



(11) **EP 0 986 094 A2**

(12) **EUROPEAN PATENT APPLICATION**

(43) Date of publication:
15.03.2000 Bulletin 2000/11

(51) Int Cl.7: **H01L 21/027, G03F 7/20**

(21) Application number: **99307119.0**

(22) Date of filing: **08.09.1999**

(84) Designated Contracting States:
AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU
MC NL PT SE
 Designated Extension States:
AL LT LV MK RO SI

(72) Inventors:
 • Kochi, Tetsunobu
 Ohta-ku, Tokyo (JP)
 • Saitoh, Kenji
 Ohta-ku, Tokyo (JP)

(30) Priority: **10.09.1998 JP 27248498**

(74) Representative:
Beresford, Keith Denis Lewis et al
BERESFORD & Co.
 High Holborn
 2-5 Warwick Court
 London WC1R 5DJ (GB)

(71) Applicant: **CANON KABUSHIKI KAISHA**
 Tokyo (JP)

(54) **Exposure method and device manufacturing method using the same**

(57) An exposure method and a device to be produced thereby are disclosed, wherein the method includes printing, by an exposure, a fine pattern onto a substrate, and printing, by an exposure, a mask pattern having a smallest linewidth larger than that of the fine pattern, onto the substrate, wherein the fine pattern and

the mask pattern are printed on the substrate superposedly, and wherein a fine pattern exposure region in which the fine pattern is to be printed has a size that includes a chip-inside-device forming region in which a chip-inside-device is to be formed in a single chip region to be formed on the substrate.

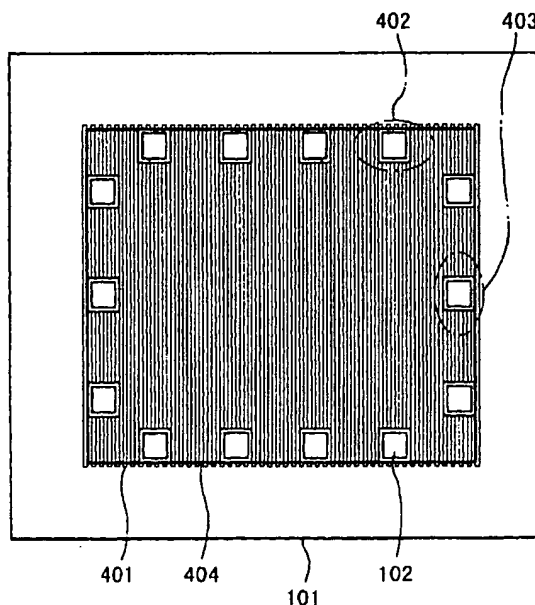


FIG. 4

BEST AVAILABLE COPY

EP 0 986 094 A2

Description

FIELD OF THE INVENTION AND RELATED ART

[0001] This invention relates generally to an exposure method. More particularly, the invention is concerned with an exposure method wherein a first exposure process as can be represented by a standard or ordinary exposure process, such as projection exposure, and a second exposure process of higher resolving power than the first exposure process, are performed so that different types of patterns are printed superposedly to thereby form a desired pattern (hereinafter "goal pattern") of smallest linewidth corresponding to the second exposure process. The present invention is suitably applicable to manufacture of chips or devices such as semiconductor chips (e.g., ICs or LSIs), detecting devices (e.g., magnetic heads), micro-machines or image pick-up devices (e.g., CCDs), for example.

[0002] Currently, many projection exposure apparatuses for manufacture of devices such as ICs, LSIs or liquid crystal panels, for example, based on photolithography, use a light source of an excimer laser. However, mere use of such excimer laser as a light source in a projection exposure apparatus does not assure production of a fine pattern of a linewidth of 0.15 micron or narrower.

[0003] In order to improve the resolution, theoretically, the numerical aperture (NA) of a projection optical system may be enlarged or the wavelength of exposure light may be shortened. Practically, however, enlargement of the NA or reduction in wavelength of the exposure light is not very easy. For, the depth of focus of a projection optical system is inversely proportional to the square of the NA while it is proportional to the wavelength λ . Because of this, enlarging the NA of a projection optical system results in a decrease of the depth of focus, which causes a difficulty of focusing and a decrease of productivity. Further, most glass materials have an extraordinarily low transmission factor with respect to a deep ultraviolet region. Even for a fused silica (quartz) which is used with a wavelength $\lambda = 248$ nm (KrF excimer laser), the transmission factor reduces almost to zero when used with a wavelength $\lambda = 193$ nm or less. Currently, no glass material has been developed that can be practically used in a region of exposure wavelength $\lambda = 150$ nm or less, corresponding to a fine pattern of 0.15 micron linewidth or less to be produced in accordance with a standard or ordinary exposure process.

[0004] Japanese Patent Application, Application No. 304232/1997, (hereinafter, "the earlier Japanese patent application"), filed by the assignee of the subject application, proposes a dual exposure process which is based on a combination of dual-beam interference exposure and standard exposure, wherein a multiple-value exposure amount distribution is applied to a substrate, to be exposed, to assure high resolution expo-

sure. In an embodiment disclosed in the earlier Japanese patent application, the dual-beam interference exposure process is performed by use of a phase shift mask having a line-and-space (L&S) pattern of 0.1 micron linewidth, and a fine linear pattern is printed through coherent illumination. Thereafter, an ordinary exposure process (for example, an exposure process based on partially coherent illumination) is performed while using a mask which is formed with a pattern having portions of different transmission factors and having a shape corresponding to an actual device pattern of smallest linewidth of 0.1 micron. In accordance with the method disclosed in the earlier Japanese patent application, a pattern of smallest linewidth of 0.10 micron may be formed through the ordinary exposure process and by using a projection exposure apparatus having a projection optical system which has an image side NA of 0.6.

[0005] Another method for the fine pattern printing is a probe exposure method wherein a pattern is drawn and printed on a photosensitive member by using a probe. The probe may be based on AFM using an interatomic force, STM using a tunnel current, an electron beam, a laser beam or proximity light, for example. However, performing the probe exposure over the whole exposure area has a disadvantage of low throughput. In consideration of it, those portions of a goal pattern that can be produced through an ordinary exposure process may be photoprinted by using a light quantity larger than an exposure threshold of a photosensitive substrate. On the other hand, those portions of insufficient resolution may be photoprinted by superposed printing which is based on an ordinary exposure and a probe exposure, with the respective light quantities each being lower than the exposure threshold of the photosensitive material but both, when combined, being higher than the exposure threshold. As a result, a multiple-value exposure amount distribution similar to that described above is applied (Japanese Patent Application, Application No. 137476/1998).

SUMMARY OF THE INVENTION

[0006] It is an object of the present invention to provide an improved exposure method by which a multiple exposure process such as described above can be applied to assure higher precision production of a device such as a semiconductor chip, for example.

[0007] These and other objects, features and advantages of the present invention will become more apparent upon a consideration of the following description of the preferred embodiments of the present invention taken in conjunction with the accompanying drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

[0008] Figure 1 is a schematic view for explaining an example of the structure of a semiconductor chip, ac-

cording to an embodiment of the present invention.

[0009] Figure 2 is a schematic view for explaining an example of the structure of an output buffer circuit in the semiconductor chip of Figure 1.

[0010] Figure 3 is a schematic view for explaining an example of the structure of an input buffer circuit of the semiconductor chip of Figure 1.

[0011] Figure 4 is a schematic view for explaining an example of the shape and structure of a fine linear pattern which can be used for formation of a fine pattern corresponding to the output and input buffer circuits of the semiconductor chip of Figure 1.

[0012] Figure 5 is a schematic view for explaining the state of exposure, in a case where a fine linear periodic pattern region and a goal pattern region coincide with each other.

[0013] Figure 6 is a schematic view for explaining the state of exposure, in a case where a fine linear periodic pattern region is magnified, as compared with a goal pattern region, in opposite directions along the direction of array of the fine linear pattern and by an amount corresponding to four lines of the fine linear pattern.

[0014] Figures 7A and 7B are graphs, respectively, for explaining the width of exposure amount that can be resolved by the dual exposure method of Figures 5 and 6.

[0015] Figure 8 is a graph for explaining the relation between the length of a pattern to be formed through the dual exposure and an increase in length where a fine linear pattern is enlarged in the lengthwise direction beyond a goal pattern region.

[0016] Figure 9 is a schematic view for explaining an example of the structure where the angle of the output buffer circuit in the semiconductor chip of Figure 1 differs from that of Figure 3 by 90 deg.

[0017] Figure 10 is a schematic view for explaining an example of the structure of a pad portion in a semiconductor chip according to a second embodiment of the present invention.

[0018] Figure 11 is an enlarged view of an upper right portion of the semiconductor chip of Figure 10.

[0019] Figure 12 is a schematic view for explaining an example where a fine pattern is placed inside a semiconductor chip.

[0020] Figure 13 is a schematic view for explaining another example where a fine pattern is placed inside a semiconductor chip.

[0021] Figure 14 is a schematic view for explaining a further example where a fine pattern is placed inside a semiconductor chip, together with a void portion.

[0022] Figure 15 is a schematic view for explaining an example of the structure of a matrix type photoelectric converting device, which can be produced in accordance with a multiple exposure process of the present invention.

[0023] Figure 16 is a schematic view for explaining an example of the layout of a fine linear pattern, for forming a fine pattern of a chip-inside-device, in the device of Figure 15.

[0024] Figures 17A, 17B and 17C are schematic views, respectively, for explaining a process for forming a silicon active region.

[0025] Figures 18A and 18B are schematic views, respectively, for explaining the principle of dual exposure process.

[0026] Figures 19A, 19B and 19C are schematic views, respectively, for explaining the principle of dual exposure process.

[0027] Figures 20A and 20B are schematic views, respectively, for explaining an exposure pattern in fine linear exposure.

[0028] Figures 21A and 21B are schematic views, respectively, for explaining an exposure pattern in dual exposure, corresponding to a portion without a rough pattern.

[0029] Figures 22A and 22B are schematic views, respectively, for explaining an exposure pattern in ordinary projection exposure.

[0030] Figure 23 is a schematic view of an example of a mask to be used for dual exposure by which a defocused image is superposed.

[0031] Figures 24A, 24B, 24C and 24D are schematic views, respectively, for explaining an exposure pattern to be formed through dual exposure.

[0032] Figures 25A and 25B are schematic views, respectively, for explaining the principle of triple exposure for forming a contact region.

[0033] Figures 26A, 26B and 26C are schematic views, respectively, for explaining the principle of the triple exposure.

[0034] Figures 27A, 27B and 27C are schematic views, respectively, for explaining the procedure for forming a wiring region.

[0035] Figure 28 is a flow chart for explaining the procedure for manufacturing a microdevice.

[0036] Figure 29 is a flow chart for explaining details of a wafer process, included in the procedure of Figure 28.

DESCRIPTION OF THE PREFERRED EMBODIMENTS

[0037] In some preferred embodiments of the present invention to be described below, a fine pattern and a pattern (hereinafter "rough pattern") having a smallest linewidth (upon a substrate) larger than that of the fine pattern, are printed on the substrate superposedly, by which a goal pattern having a smallest linewidth corresponding to that of the fine pattern, is formed on the substrate. This exposure method is called in this specification a "dual exposure" or "multiple exposure". In this exposure method, the region on which the fine pattern is to be printed is exposed with a size that contains the whole chip-inside-device forming region, upon one chip to be produced on a substrate, where a chip-inside-device is to be formed.

[0038] Here, the term "chip-inside-device forming re-

gion" refers to such region that includes all of or any one of (i) an active element such as an MOS transistor, a bipolar transistor or a diode, for example, (ii) a passive element such as a resistance element or a capacitance element, for example, and (iii) a connection region for electrical connection of the active element or the passive element.

[0039] When the dual exposure is to be performed, a fine pattern should desirably be uniform as much as possible.

[0040] In the embodiments of the present invention to be described below, a fine-pattern exposure region is made larger than a chip-inside-device forming region. This enables that a portion not influenced by a micro-loading effect, a proximity effect or an edge effect of the edge of the fine pattern, that is, a portion where the fine pattern is uniform in shape, is used in the chip-inside-device forming region.

[0041] Further, if the whole surface of a fine-pattern exposure region is exposed in a single exposure, in connection with the exposure amount, the exposure amount distribution control in a wide range as well as the state after the resist exposure (e.g., oxide diffusion) can be uniformed. Particularly, while in a chemical amplification type resist the time from the exposure to the development has a large influence to the linewidth (CD), this can be made uniform.

[0042] The fine pattern in the chip-inside-device forming region can be made uniform through the procedure described above. The reproducibility of a goal can therefore be improved, and thus various devices such as a semiconductor chip, for example, can be manufactured very precisely.

[0043] Preferred embodiments of the present invention will now be described with reference to the accompanying drawings.

[Embodiment 1]

[0044] A semiconductor chip is provided with pads at its outer peripheral portion, for transmission and reception of signals to and from the outside of the chip. Figure 1 shows an example, wherein denoted at 101 is a semiconductor chip which is formed on a semiconductor wafer or substrate, and denoted at 102 are pads formed at the outer peripheral portion of the chip. For transmission and reception of a greater amount of information, there are cases where pads are formed along all the four peripheral sides of the chip, such as shown in the drawing.

[0045] For example, in a case of a logic integrated circuit, such a semiconductor chip has output pads each having a buffer circuit to which a single-stage or multiple-stage inverter circuit (signal inverting circuit) for driving a large load outside the chip is connected. Also, its input pads have a buffer circuit for driving the inside circuit.

[0046] Figure 2 illustrates an example of an output pad having an output buffer circuit. For convenience in

explanation, an example of a pad with a single-stage inverter buffer circuit will be described. Denoted in Figure 2 at 10 is a P type MOS transistor. Denoted at 1 is a source region of the P type MOS transistor, and denoted at 2 is a drain region of the P type MOS transistor. Denoted at 20 is an N type MOS transistor. Denoted at 3 is a source region of the N type MOS transistor, and denoted at 4 is a drain region of the N type MOS transistor. Denoted at 5 is a gate electrode which is used for both of the P type and N type MOS transistors. Denoted at 6 are contacts for connecting the sources and drain regions 1 - 4 with a wiring layer (wire 8, electric source wire 9 and ground wire 11). Denoted at 7 is a pad for connecting the semiconductor chip with the outside. The drain regions 2 and 4 are connected to the wire 8 through the contacts 6, and the wire 8 is connected to the pad 7. The source region 1 of the P type MOS transistor 10 is connected to the electric source wire 9 through the contact 6. The source region 3 of the N type MOS transistor 20 is connected to the ground wire 11 through the contact 6. The sources and drain regions 1 - 4 are defined in a silicon active layer at the surface of the silicon substrate, and the wiring layer is formed on an insulating layer (not shown) which is provided on the silicon active layer. The gate electrode 5 is provided by a polysilicone layer, a polycide layer or an accumulation of these layers. With the structure described above, the P type MOS transistor 10 and the N type MOS transistor 20 provide a CMOS inverter. In accordance with a signal transmitted to the gate electrode 5 from an inside circuit (not shown) and through the gate wire 12, an inversion signal thereof is outputted to the pad 7.

[0047] Figure 3 illustrates an example of an input pad having an input buffer circuit. In Figure 3, like numerals as those of Figure 2 are assigned to corresponding elements. With the structure as illustrated, in response to application of a signal from the outside to the pad 7, the signal is transmitted to the gate electrode 5 through the gate wire 12, whereby a signal as being inverted by the CMOS inverter is transmitted to the inside circuit (not shown).

[0048] Figure 4 illustrates an example of a pattern shape, upon a semiconductor wafer, of a fine linear pattern (a stripe-like fine pattern) in a case where a fine MOS transistor is to be produced in an output buffer circuit and an input buffer circuit of a semiconductor chip on the semiconductor wafer through a convenient process. The production is based on a multiple exposure method wherein a fine linear pattern and a rough pattern having a smallest linewidth, upon a semiconductor wafer or substrate (or as the same is printed on the semiconductor wafer), larger than that of the fine linear pattern are printed on the substrate superposedly, whereby a goal pattern having a smallest linewidth corresponding to that of the fine linear pattern is produced on the wafer.

[0049] In Figure 4, like numerals as those of Figure 1 are assigned to corresponding elements. Denoted at 401 is a fine linear pattern (periodic pattern). A rough

pattern for producing a gage layer, for example, may be formed so that it can be overlapped with the fine linear pattern 401 and, through the dual exposure process, an MOS transistor having a fine gate length can be produced conveniently. In this embodiment, the pattern forming region for forming the fine linear pattern 401 includes input and output buffer circuits, and the whole surface thereof is formed (exposed) into a size slightly larger than a chip-inside-device forming region 404 of the semiconductor chip 101.

[0050] Here, the term "chip-inside-device forming region" refers to such region that includes all of or any one of (i) an active element such as an MOS transistor, a bipolar transistor or a diode, for example, (ii) a passive element such as a resistance element or a capacitance element, for example, and (iii) a connection region for electrical connection of the active element or the passive element. In the example of Figure 1, it is the region of the semiconductor chip 101 that includes an inside circuit, a peripheral circuit and a connection region for connecting them. In the examples of peripheral circuits shown in Figures 2 and 3, it corresponds to a region including P type MOS transistor 10, N type MOS transistor 20, contacts 6 for connecting the transistors 10 and 20 with wires 8, 9 and 11, and a contact (not shown) for connecting the gate 5 (Figure 3) of the MOS transistors 10 and 20 with the pad 7. The position of the chip-inside-device forming region is not restricted by the placement of the pad 102. A chip-inside-device forming region may be defined in a region between the pad and the outer periphery of the semiconductor chip. Also, the position of the pad is not limited to the proximity to the chip outside periphery. It may be placed close to the center of the chip.

[0051] In a fine linear pattern, due to the influence of the edge effect, the proximity effect or the micro-loading effect, the exposure amount or the resolution decreases at the opposite ends with respect to the direction of its array or its length. In accordance with this embodiment, however, the pattern forming region for forming the fine linear (periodic) pattern 401 is defined by the whole surface exposure to a size notably larger than the chip-inside-device forming region of the semiconductor chip 101, which provides an input/output buffer circuit. As a result of this, the end portion of the fine linear pattern having a lower exposure amount or resolution is positioned outside the chip-inside-device forming region. Therefore, in the chip-inside-device forming region, only a portion of the fine pattern which is uniform in respect to shape can be used. This enables that not only the inside circuit portion of the chip 101 but also the input/output buffer circuit are produced very precisely.

[0052] Figures 5 and 6 illustrate a difference in respect to the setting of a fine periodic pattern region and a goal pattern (five-bar) region. Figure 5 shows an intensity distribution in the dual exposure in a case where the fine periodic pattern region is set in the same region as the goal pattern to be produced. Figure 6 shows an

intensity distribution in the dual exposure in a case where the fine periodic pattern region is enlarged so that a goal pattern can be produced satisfactorily. In each of Figures 5 and 6, the upper portion shows exposure amount distributions of a fine periodic pattern, using a Levenson type phase shift mask. The middle portion shows exposure amount distributions provided by a rough pattern. The lower portion shows exposure amount distributions provided by the dual exposure. The exposure amount distributions are illustrated in respect to various levels of defocus, varying along the lateral direction in the drawing. In these drawings, exposure amount distributions as well as the positions of the five bars are illustrated.

[0053] In the example of Figure 5, particularly when a defocus occurs, the line shape of the fine periodic pattern at its opposite ends is distorted. Also, as regards the exposure amount distribution provided by the dual exposure, there is a large difference between a central pattern and patterns at the end portions. As compared therewith, in the example of Figure 6 wherein the fine pattern is set larger than the goal pattern region by four bars at each end, even if a defocus occurs, the difference in exposure amount distribution (after the dual exposure) between the central pattern and patterns at the opposite ends is smaller. Thus, it is seen that the exposure latitude is improved.

[0054] This will be described in more detail, in connection with an example of a defocus of 0.4 micron. Figures 7A and 7B show a resolvable exposure amount range. In a case where the region for the goal pattern coincides with the fine periodic pattern region, as shown in Figure 7A, although the five bars are resolved, the linewidth of each bar varies. As compared therewith, if the fine periodic pattern region is enlarged, as shown in Figure 7B, all the five bars can be resolved into a desired linewidth. Also, there is a certain range for exposure amount that enables resolution with the desired linewidth.

[0055] Figures 5, 6, 7A and 7B show results of exposure where the fine periodic pattern and the five bars have a linewidth and a spacing of 0.12 micron, and where an ordinary exposure process is performed by use of a projection exposure apparatus which comprises a light source of a KrF excimer laser ($\lambda = 248$ nm) and a projection optical system having an image side NA of 0.6. Table 1 below shows preferable enlargement amounts (pattern bar number) of a fine periodic pattern, in a case where a projection exposure apparatus such as described above is used for the ordinary exposure process and the linewidth and spacing are set to 0.12 micron, 0.13 micron and 0.15 micron, respectively, and in a case where the number of bars of a goal pattern is set, in regard to isolated pattern, to one, three and five, respectively. In Table 1, the pattern bar number corresponds to the number of glass patterns in a case of a void pattern (the pattern is light transmissive) and to the number of Cr patterns in a case of a residual pattern (the

pattern is light blocking).

TABLE 1

PATTERN WIDTH	0.12	0.13	0.15
PATTERN BAR NUMBER			
1	3	2	1
3	4	3	2
>3	4	3	2

[0056] As described above, in the case where the linewidth of a fine periodic pattern is 0.12 micron, it is effective in dual exposure to enlarge the fine periodic pattern region by four periodic pattern bars or more as compared with the goal pattern region.

[0057] Further, investigations have been made on how much the periodic pattern region should be enlarged in regard to the lengthwise direction of the pattern. Figure 8 is a graph showing the increase in length of a fine periodic pattern (enlargement in the lengthwise direction) and the length of the pattern to be produced through the dual exposure. Here, the smallest linewidth of the fine periodic pattern is w , and the length of a bar pattern to be formed through the dual exposure of a goal pattern (bar pattern) having a width w and a length $14w$ is illustrated in terms of percent (%). In a case where the lengthwise direction of the fine periodic pattern is the same as the goal pattern, the length of a pattern produced as a result of dual exposure is shortened by about 14% as compared with the goal pattern. It is seen that, with enlargement of the fine periodic pattern along its lengthwise direction, the amount of shortening is reduced and that the shortening is substantially saturated at 6 times the smallest linewidth. It is therefore preferable that, in regard to the lengthwise direction, the fine periodic pattern is enlarged by 6 times the smallest linewidth (0.72 micron in case of smallest linewidth of 0.12 micron) or more.

[0058] In summary, the fine periodic pattern exposure region should desirably be enlarged, at its opposite ends, by four bars or more with respect to the periodic direction as compared with the goal pattern region (device forming region), and be enlarged by 6 times or more the smallest linewidth with respect to the lengthwise direction.

[Embodiment 2]

[0059] In a case where, as shown in Figure 4, all the gate patterns are formed by one and the same type of pattern (fine linear pattern), the pad in the region 402 may be formed in accordance with the layout such as shown in Figure 2 or 3. However, in regard to the pad of the region 403, the orientation of the buffer circuit will be deviated from the pad by 90 deg. as shown in Figure 9. As a result, depending on the pad array, the length of the electric source wire 9 connecting the buffer circuit

varies. This causes a difference in series resistance and, thus, a difference in operation speed of the buffer circuit.

[0060] Further, while there are a voltage source wire and a ground wire 11 around the pad such as shown in Figure 2, 3 or 9, if the size of the inverter is large or plural inverters are connected in multiple stages, the size of one side of the buffer circuit may become larger than the size of the pad. In that occasion, depending on the orientation of the buffer circuit, the element may not be placed efficiently between these wire regions, which may cause an increase in chip size.

[0061] Figure 10 illustrates an example of the structure of a pad in a semiconductor chip according to a second embodiment of the present invention. This embodiment is based on a multiple exposure method in which a fine linear pattern and a rough pattern having a smallest linewidth larger than the linewidth of the fine linear pattern are printed superposedly, such that a goal pattern having a smallest linewidth corresponding to the linewidth of the fine linear pattern is produced. Specifically, in this embodiment, there are plural fine linear patterns having at least two different angles. Thus, this embodiment provides a further improvement to the first embodiment described hereinbefore.

[0062] In Figure 10, like numerals as those of Figure 1 are assigned to corresponding elements. Denoted in Figure 10 at 601 is a first fine linear pattern group, and denoted at 602 is a second fine linear pattern group which defines a right angle to the first fine linear pattern group 601. When a gate for a buffer circuit is formed by use of the fine linear pattern shown in Figure 10, the relative positional relation between a pad and a corresponding buffer circuit can be held constant, at all the peripheral sides of the semiconductor chip. Figure 11 is an enlarged view of the right upper portion of the chip of Figure 10. As shown in the drawing, the orientation of the fine linear pattern may be changed in accordance with the placement of the pad, to thereby change the orientation of the MOS transistor. In this manner, a number of buffer circuits of uniform operation characteristic can be disposed in large integration.

[Embodiment 3]

[0063] The present invention is not limited to pads, but it is applicable also to placement of transistors inside a semiconductor chip.

[0064] Figures 12, 13 and 14 show examples wherein fine patterns are formed also inside a semiconductor chip. As shown in Figure 12, fine patterns may be formed throughout the whole surface of a fine-pattern exposure region. Also, as shown in Figure 14, the patterns may be formed in the fine-pattern exposure region, except an inside portion thereof. In Figure 14, denoted at 1801 is a void region without a fine linear pattern. As shown in Figures 12 - 14, plural fine linear pattern groups having different array directions may be formed.

In Figures 12 - 14, the first fine linear pattern 1601 or 1701 and the second fine linear pattern 1602 or 1702 are arrayed in orthogonal directions.

[Embodiment 4]

[0065] Figure 15 shows an example wherein the concept of the second embodiment is applied to a matrix type photoelectric converting device which can be formed on a semiconductor wafer (substrate) as a single device. Denoted in Figure 15 at 801 is a photoelectric converting element region in which photoelectric converting elements are arrayed in matrix. Denoted at 802 is a vertical scan circuit, and denoted at 803 is a horizontal scan circuit. Denoted at 804 is a horizontal reading circuit, and denoted at 805 is an output amplifier.

[0066] Electric charges as produced by photoelectric converting elements are directly read out by the horizontal reading circuit 804, or they are read out after being amplified by amplifying elements which are provided in association with the photoelectric converting elements, respectively, in an order as determined by the selection through the vertical scan circuit 802. After this, in the order as selected by the horizontal scan circuit 803, they are read out sequentially through the output amplifier 805.

[0067] Here, the vertical scan circuit 802 functions to perform sequential selection in vertical direction, and, for it, generally a combination of a CMOS inverter and a transfer switch or a combination of an N or P type MOS transistor and a capacitance element is known. On the other hand, the horizontal scan circuit 803 has a circuitry similar to that of the vertical scan circuit 802, but the scan direction thereof differs from that of the vertical scan circuit 802 by 90 deg. For this reason, in respect to large integration and efficient placement, it is necessary that the MOS transistors constituting the circuits 802 and 803 have orientations being different by 90 deg. from each other.

[0068] Figure 16 shows the shape of a fine linear pattern for accomplishing the circuit of this embodiment. Denoted in the drawing at 901 is a first fine linear pattern group, and denoted at 902 is a second fine linear pattern group having its orientation different from the first fine linear pattern group by 90 deg. The first fine linear pattern group 901 is used to form a gate portion of an MOS transistor which constitutes the vertical scan circuit 802, while the second fine linear pattern group 902 is used to form a gate portion of an MOS transistor which constitutes the horizontal scan circuit 803. This enables efficient placement of circuits.

[0069] Another example of a circuit which performs similar matrix driving is a liquid crystal display device, and, as a matter of course, similar advantageous results are attainable in that case. In place of a sequential scan circuit, a decoder circuit may be used. Also in such case, similar advantageous results are obtainable. Further, similar advantageous results can be attained in cases

of memories such as DRAM, SRAM, or flash memory, for example.

[0070] Further, this embodiment is applicable also to manufacture of mechanical devices such as a micromachine, for example, not only to a semiconductor device.

[0071] While the example described above concerns a case where fine linear patterns are arrayed horizontally (0 deg.) and vertically (90 deg.) as viewed in the drawing, the present invention is not limited to this arrangement. Any other angles may be used. Further, different fine linear patterns having three or more different orientations may be used in accordance with a circuitry to be produced.

15 [Embodiment 5]

(Manufacture of Device Structure)

[0072] Figures 17A through 25B are schematic views for explaining the procedure for manufacturing a chip-inside-device structure according to the present invention, on the basis of the multiple exposure method.

[0073] Figures 17A - 17C show a process for forming a silicon active region. A mask pattern such as shown in Figure 17A may be exposed by using an ordinary projection exposure apparatus having an exposure wavelength $\lambda = 248$ nm (KrF excimer laser) and a projection optical system with an image side NA of 0.6, whereby a photoresist pattern with a portion corresponding to the silicon active region being remained may be formed on a semiconductor wafer. Then, a silicon oxide film region may be formed outside that pattern by using a selection oxidation method (LOCOS), for example. This region may function as a device separation region, such that a silicon active region can be produced. Figure 17B is a plan view thereof, and Figure 17C is a sectional view taken along a line A - A' in Figure 17B. In Figures 17A - 17C, denoted at 1001 is a silicon active region which can thus be formed, and denoted at 1002 is a device separation region which comprises an electrically insulating layer.

[0074] Figures 18A and 18B as well as Figures 19A - 19C illustrate the principle of dual exposure method for forming a gate region. Figure 18A shows a Levenson pattern having a linewidth and a spacing of L, as being printed on a semiconductor wafer. Figure 18B shows a rough pattern. The rough pattern comprises a pattern region 1101 having a transmission factor 1, and a pattern region 1102 having a transmission factor 2. The smallest linewidth and spacing of these pattern regions, as being printed on the semiconductor wafer, are set to 2L or more. The Levenson pattern and the rough pattern are photoprinted superposedly on a substrate as shown in Figure 19A, in accordance with the dual-beam interference exposure method and the standard or ordinary exposure method as described hereinbefore. Here, the exposure threshold E_{th} of the photoresist on which these patterns are printed as well as the patterns and the ex-

posure amounts in the pattern regions are set in an appropriate relation with each other. As a result, a photoresist pattern (goal pattern) such as a pattern 1103 shown in Figure 19B which corresponds to a gate having a smallest linewidth L , in the state being printed on the semiconductor wafer, can be produced. Here, the transmission factors 1 and 2 are referred to only for convenience in explanation, and they have no specific physical significance.

[0075] A gate insulation film may then be formed on the silicon active region 1001 (Figures 17B and 17C) by thermal oxidation of the silicon. Thereafter, a polysilicon layer may be formed through a CVD (chemical vapor deposition) method, for example. The polysilicon layer may then be etched and patterned in accordance with the photoresist pattern having been formed through the dual exposure method described above, whereby a gate pattern of a smallest linewidth L can be formed. Figure 19B is a plan view of it, and Figure 19C is a sectional view taken along a line A - A' in Figure 19B. In Figures 19B and 19C, denoted at 1103 is a gate region of polysilicon, for example, and denoted at 1104 is a gate insulation film. Denoted at 1105 is a source and a drain region of an MOS transistor, which are formed by impurity injection based on the ion injection method performed after the formation of the gate region 1103.

[0076] The principle of dual exposure in the embodiment described above will be explained in greater detail, with reference to Figures 20A through 22B. In the dual exposure process, as compared with the ordinary exposure sensitivity setting, as shown in Figures 20A - 21B, where the maximum exposure amount in the periodic pattern exposure (Levenson pattern exposure or dual-beam interference exposure, for example) is taken as 1, the exposure threshold value E_{th} of a resist of a photosensitive substrate is set to be larger than 1. In this photosensitive substrate, when an exposure pattern (exposure amount distribution) as defined by the periodic pattern exposure only is developed, the exposure amount is insufficient. Therefore, while there may be a small variation in film thickness, a portion having a zero film-thickness is not produced as a result of the development, and no lithographic pattern is produced by the etching. Thus, this can be regarded as disappearance of a periodic pattern. Here, the dual exposure will be explained below with reference to an example where a negative type photoresist is used, the dual exposure process can be used with a positive type photoresist. Figures 20A and 21A show a lithography pattern (nothing is produced), and Figures 20B and 21B show the relation between the exposure amount distribution and the exposure threshold. The reference character E_1 in Figures 20B and 21B denotes the exposure amount in the periodic pattern exposure, and the reference character E_2 denotes the exposure amount in the ordinary projection exposure.

[0077] The dual exposure process has a feature that an exposure pattern of high resolution which may ap-

parently disappear only through the periodic pattern exposure is mixed with an exposure pattern of desired shape, including a pattern of a size not larger than the resolving power of the ordinary projection exposure, such that only a desired portion of a resist is selectively exposed by an amount not lower than the exposure threshold of the resist, whereby a desired lithographic pattern can be finally produced.

[0078] Figure 22A shows an exposure pattern provided by ordinary projection exposure. In this embodiment, the resolution of ordinary projection exposure is set to be about a half of that of the dual-beam interference exposure for the periodic pattern exposure. Thus, the linewidth of the exposure pattern by the projection exposure as illustrated is about twice the linewidth of an exposure pattern by the dual-beam interference exposure.

[0079] When the projection exposure for forming the exposure pattern of Figure 22A is performed, after the dual-beam interference exposure and without intervention of a development process, superposedly to the same region of the same resist, the total exposure amount distribution on the resist will be such as shown in the graph at the bottom of Figure 22B. Here, since the ratio between the exposure amount E_1 of dual-beam interference exposure and the exposure amount E_2 of the projection exposure is set at 1:1 while the exposure threshold E_{th} of the resist is set within a range between the exposure amount E_1 ($= 1$) and the sum ($= 2$) of the exposure amount E_1 and the exposure amount E_2 of the projection exposure, a lithographic pattern such as shown at the upper portion of Figure 22B can be formed. The isolated linear pattern shown in the upper portion of Figure 22B has a resolution corresponding to that of the dual-beam interference exposure, and there is no simple periodic pattern. Thus, a high resolution pattern having a resolution higher than that as can be attained by the ordinary projection exposure, is produced on the semiconductor wafer.

[0080] In addition to the method described above, there are some other methods for multiple exposure process. Another example will be described below.

[0081] Figure 23 shows a rough pattern mask with which a defocused image of a fine pattern, that can not be resolved by ordinary exposure, is superposed.

[0082] This mask has a pattern directly corresponding to a gate having a smallest linewidth L , as being printed on a semiconductor wafer. When the ordinary exposure is performed with this mask, while the region of a linewidth L or more can be resolved, as regards the region of the smallest linewidth, a blurred exposure amount distribution is formed on the resist.

[0083] The exposure amount distribution in this portion (B - B') will be described below in detail.

[0084] Figure 24A shows an exposure pattern in the ordinary exposure, and Figure 24B shows the state of exposure corresponding to it. Since this exposure pattern is a fine pattern smaller than the resolving power of

the exposure apparatus, it can not be resolved. Thus, the intensity distribution on the substrate being exposed is blurred and expanded. Here, the exposure pattern comprises a fine pattern having a linewidth about a half of the resolution power of the ordinary projection exposure.

[0085] The projection exposure for forming the exposure pattern of Figure 24C is performed, after the periodic pattern exposure of Figure 20A and without intervention of a development process, superposedly to the same region of the same resist. At that time, the center of the ordinary exposure pattern is registered with the peak of the periodic pattern. Then, the total exposure amount distribution on the resist will be such as shown in the graph of Figure 24D. Here, since the ratio between the exposure amount E_1 of the periodic pattern exposure and the exposure amount E_2 of the projection exposure is set at 1:1 while the exposure threshold E_{th} of the resist is set within a range between the exposure amount E_1 ($= 1$) and the sum ($= 2$) of the exposure amount E_1 and the exposure amount E_2 of the projection exposure, as a result of a development process, a lithographic pattern such as shown in Figure 24C is formed on the semiconductor wafer. The isolated linear pattern shown in Figure 24C has a resolution corresponding to that of the periodic pattern exposure, and a simple periodic pattern itself is not developed. Thus, a high resolution pattern having a resolution higher than that as can be attained by the ordinary projection exposure, is produced. It is to be noted that the exposure amounts 1 and 2 are referred to only for convenience in explanation, and they have no specific physical significance.

[0086] Figures 25A and 25B illustrate the principle of the triple exposure method, for forming a contact region. First, a Levenson pattern which comprises a stripe-like pattern having a linewidth and a spacing of L , when printed on a semiconductor wafer, is photoprinted by use of an exposure apparatus according to the dual-beam interference exposure method and with an exposure amount 1. Subsequently, the Levenson pattern as being rotated by 90 deg. is photoprinted with an exposure amount 1. As a result of the above, the semiconductor wafer is exposed in the state such as shown in Figure 25B. In Figure 25B, denoted at 1201 are those regions (Levenson double exposure regions) having been exposed twice through the Levenson pattern. Denoted at 1202 are those regions (Levenson single exposure regions) having been exposed once through the Levenson pattern. Denoted at 1203 are those regions (Levenson unexposed regions) not having been exposed during the Levenson pattern exposure. Each Levenson double exposure region 1201 has been exposed with an exposure amount 2. The exposure amount 2 has been set to a level lower than the exposure threshold E_{th} of a photoresist applied to the substrate to be exposed.

[0087] After printing two orthogonal Levenson patterns upon the substrate in the manner described

above, a rough mask pattern 1204 such as shown in Figure 26A is printed in accordance with the ordinary exposure process and with an exposure amount 1. As a result of this, only those portions having been exposed superposedly by the Levenson double exposures 1201 and the rough mask pattern 1204 exposure, have been exposed with an exposure amount 3. Here, the exposure amounts of respective patterns may be so determined that the exposure threshold E_{th} of the photoresist is at a level between the exposure amount 2 and the exposure amount 3. On the basis of this, a photoresist pattern of square shape having each side of a length L can be produced. Here, the exposure amounts 1, 2 and 3 are referred to only for convenience in explanation, and they have no specific physical significance.

[0088] An inter-layer insulating film comprising a silicon oxide film, for example, may be formed on the polysilicon gate 1103 of Figure 19D in accordance with a CVD method, for example. After this, the inter-layer insulating film may be etched in accordance with the photoresist pattern formed through the triple exposure method described above, by which a contact hole 1205 can be formed. Figure 26B is a plan view of it, and Figure 26C is a sectional view taken along a line A - A' in Figure 26B. In Figures 26B and 26C, denoted at 1205 is a contact hole, and denoted at 1206 is an inter-layer insulating film.

[0089] Figures 27A - 27C show the process for forming a wiring region. The rough mask pattern shown in Figure 27A is photoprinted through the ordinary exposure method, whereby a photoresist pattern is produced. A metal layer such as aluminum may then be formed on the inter-layer insulating film 1206 and the contact hole 1205 described above, through a sputtering method, for example. Subsequently, the metal layer may be etched in accordance with the photoresist pattern formed through the ordinary exposure method described above, whereby a desired wiring pattern can be produced. The metal layer formed on the contact hole 1205 is electrically communicated with the source and drain region 1105 in the silicon active region, and electrodes of an MOS transistor are provided. Figure 27B is a plan view, and Figure 27C is a sectional view taken on a line A - A'. Denoted at 1301 is a metal wiring layer.

[Embodiment 6]

(Device Manufacturing Method)

[0090] Next, an embodiment of a semiconductor device manufacturing method which uses an exposure method according to any one of the preceding embodiments, will be explained.

[0091] Figure 28 is a flow chart of procedure for manufacture of microdevices such as semiconductor chips (e.g. ICs or LSIs), liquid crystal panels, CCDs, thin film magnetic heads or micro-machines, for example.

[0092] Step 1 is a design process for designing a cir-

cuit of a semiconductor device. Step 2 is a process for making a mask on the basis of the circuit pattern design. Step 3 is a process for preparing a wafer by using a material such as silicon. Step 4 is a wafer process (called a pre-process) wherein, by using the so prepared mask and wafer, circuits are practically formed on the wafer through lithography. Step 5 subsequent to this is an assembling step (called a post-process) wherein the wafer having been processed by step 4 is formed into semiconductor chips. This step includes an assembling (dicing and bonding) process and a packaging (chip sealing) process. Step 6 is an inspection step wherein operation check, durability check and so on for the semiconductor devices provided by step 5, are carried out. With these processes, semiconductor devices are completed and they are shipped (step 7).

[0093] Figure 29 is a flow chart showing details of the wafer process.

[0094] Step 11 is an oxidation process for oxidizing the surface of a wafer. Step 12 is a CVD process for forming an insulating film on the wafer surface. Step 13 is an electrode forming process for forming electrodes upon the wafer by vapor deposition. Step 14 is an ion implanting process for implanting ions to the wafer. Step 15 is a resist process for applying a resist (photosensitive material) to the wafer. Step 16 is an exposure process for printing the circuit pattern of the mask on the wafer in accordance with an exposure process based on the smallest linewidth to be printed, such as a multiple exposure process or an ordinary exposure process described hereinbefore, for example. Step 17 is a developing process for developing the exposed wafer. Step 18 is an etching process for removing portions other than the developed resist image. Step 19 is a resist separation process for separating the resist material remaining on the wafer after being subjected to the etching process. By repeating these processes, circuit patterns are superposedly formed on the wafer.

[0095] In this embodiment, the multiple exposure process is used for production of a gate pattern and a contact hole. However, the invention is not limited to this, but it may be applied to production of a fine wiring.

[0096] In accordance with the device manufacturing method of this embodiment, high density microdevices can be manufactured with a lower cost.

[0097] In the embodiments of the present invention described hereinbefore, the fine-pattern exposure region is made larger than the chip-inside-device forming region so that the former includes the latter. As a result, a fine pattern not influenced by the edge effect of the pattern, the proximity effect, or the micro-loading effect, can be used in the chip-inside-device forming region. Also, all the above-described fine pattern or patterns may be formed on a single mask so that it or they may be photoprinted in a single exposure operation. This accomplishes uniformness of control of the exposure amount distribution over a wide range and of the state of the resist after the exposure (e.g., oxide diffusion),

and thus high precision production of a semiconductor chip is assured. Particularly, in a chemical amplification type resist, the time from the exposure to the development has a large influence to the linewidth (CD). Therefore, making uniform the time from the exposure to the development is effective to improve the precision of a device such as a semiconductor chip, for example.

[0098] While the invention has been described with reference to the structures disclosed herein, it is not confined to the details set forth and this application is intended to cover such modifications or changes as may come within the purposes of the improvements or the scope of the following claims.

Claims

1. An exposure method, comprising the steps of:

- printing, by an exposure, a fine pattern onto a substrate; and
- printing, by an exposure, a mask pattern having a smallest linewidth larger than that of the fine pattern, onto the substrate;

wherein the fine pattern and the mask pattern are printed on the substrate superposedly, and wherein a fine pattern exposure region in which the fine pattern is to be printed has a size that includes a chip-inside-device forming region in which a chip-inside-device is to be formed in a single chip region to be formed on the substrate.

2. A method according to Claim 1, wherein the whole of the fine pattern is formed on a single mask, and wherein, through a single exposure of the substrate to the mask, the fine pattern is printed on the fine pattern exposure region.
3. A method according to Claim 1, wherein the fine pattern comprises a stripe-like pattern.
4. A method according to Claim 1, wherein the fine pattern comprises a periodic pattern having a regular periodicity.
5. A method according to Claim 4, wherein, in respect to a direction of array of the periodic pattern, the chip-inside-device forming region is placed inside the fine pattern exposure region by an amount corresponding to at least one pattern element of the periodic pattern.
6. A method according to Claim 4, wherein the periodic pattern has a pattern width of not greater than 0.15 micron and pattern elements of a number not less than 3, and wherein, in respect to a direction of array of the periodic pattern, the chip-inside-de-

vice forming region is placed inside the fine pattern exposure region by an amount corresponding to at least two pattern elements of the periodic pattern.

7. A method according to Claim 4, wherein the periodic pattern has a pattern width of not greater than 0.12 micron and pattern elements of a number not less than 3, and wherein, in respect to a direction of array of the periodic pattern, the chip-inside-device forming region is placed inside the fine pattern exposure region by an amount corresponding to at least four pattern elements of the periodic pattern. 5
8. A method according to Claim 4, wherein, in respect to a direction of the length of the periodic pattern, the chip-inside-device forming region is placed inside the fine pattern exposure region by an amount corresponding to at least 6 times the linewidth of the periodic pattern. 10 15
9. A method according to Claim 4, wherein the periodic pattern comprises a stripe-like pattern. 20
10. A method according to Claim 4, wherein the periodic pattern includes a first periodic pattern and a second periodic pattern having a direction of array being different from the first periodic pattern. 25
11. A method according to Claim 10, wherein the first and second periodic patterns are arrayed along orthogonal directions. 30
12. A method according to Claim 4, wherein the periodic pattern includes different groups of periodic patterns having different directions of array, wherein there are plural pads in the chip arrayed along first and second directions, wherein, around pads disposed along the first direction, a group of periodic patterns arrayed along the first direction are disposed, and wherein, around pads disposed along the second direction, a group of periodic patterns arrayed along the second direction are disposed. 35 40
13. A method according to Claim 4, wherein the periodic pattern includes at least three patterns having different directions of array. 45
14. A method according to Claim 1, wherein the fine pattern is formed on the whole surface of the fine pattern exposure region. 50
15. A method according to Claim 1, wherein the fine pattern is formed on the fine pattern exposure region, except for a portion inside it. 55
16. A device manufacturing method, comprising the steps of:

printing, by an exposure, a fine pattern onto a substrate;
printing, by an exposure, a mask pattern having a smallest linewidth larger than that of the fine pattern, onto the substrate;
wherein the fine pattern and the mask pattern are printed on the substrate superposedly, and wherein a fine pattern exposure region in which the fine pattern is to be printed has a size that includes a chip-inside-device forming region in which a chip-inside-device is to be formed in a single chip region to be formed on the substrate; and
developing the superposedly printed substrate for production of a device from the developed substrate.

17. A method according to Claim 16, wherein the whole of the fine pattern is formed on a single mask, and wherein, through a single exposure of the substrate to the mask, the fine pattern is printed on the fine pattern exposure region.
18. A method according to Claim 16, wherein the fine pattern comprises a periodic pattern.
19. A semiconductor device, comprising:

a substrate; and
a pattern structure formed on the substrate in accordance with a process which includes (i) printing, by an exposure, a fine pattern onto the substrate, and (ii) printing, by an exposure, a mask pattern having a smallest linewidth larger than that of the fine pattern, onto the substrate, wherein the fine pattern and the mask pattern are printed on the substrate superposedly, and wherein a fine pattern exposure region in which the fine pattern is to be printed has a size that includes a chip-inside-device forming region in which a chip-inside-device is to be formed in a single chip region to be formed on the substrate.

20. A semiconductor device according to claim 19, wherein the fine pattern comprises a periodic pattern.
21. An exposure method for forming a pattern on a pattern region of a substrate, comprising:

printing by exposure a fine pattern onto an area of the substrate including the pattern region;
printing, by exposure, a mask pattern onto the pattern region of the substrate.
22. An exposure method according to claim 20, wherein the fine pattern is a periodically repeating pattern,

and a first portion of the fine pattern has an alignment direction which differs from an alignment direction of a second portion of the pattern.

5

10

15

20

25

30

35

40

45

50

55

12

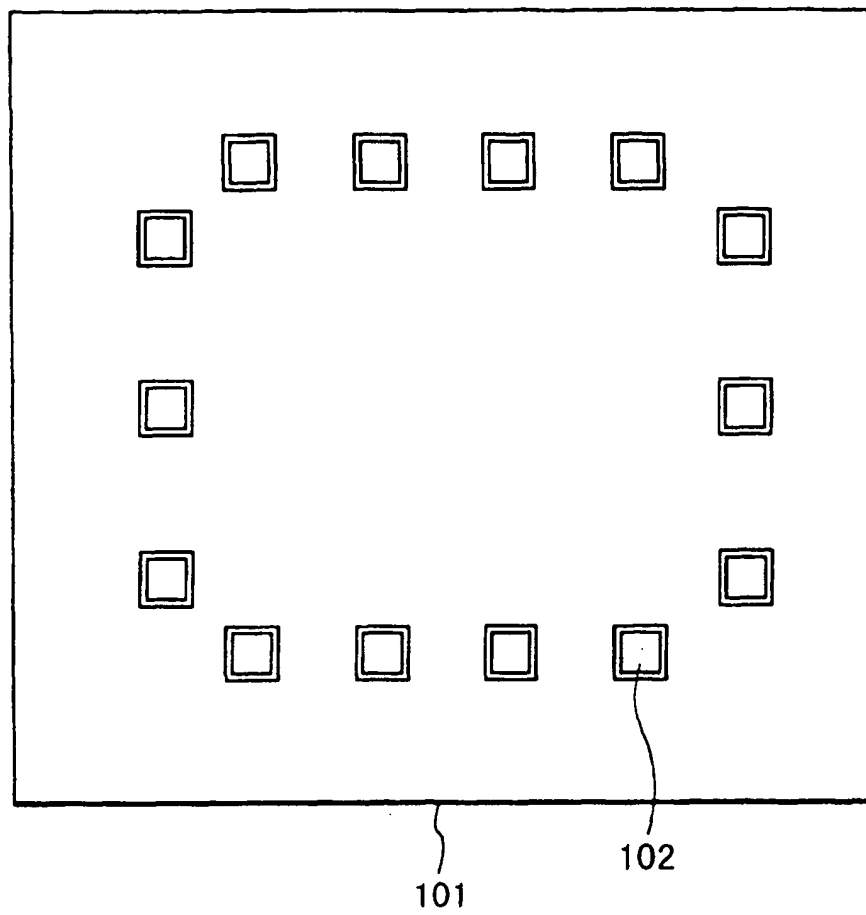


FIG. 1

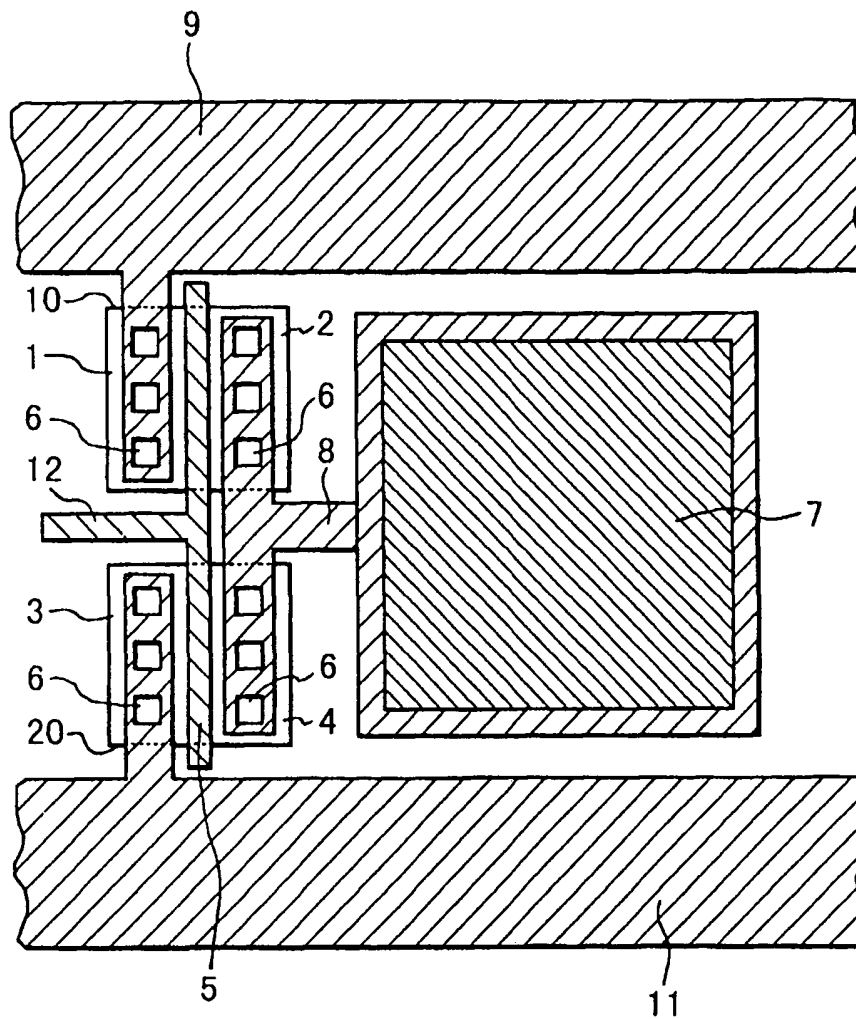


FIG. 2

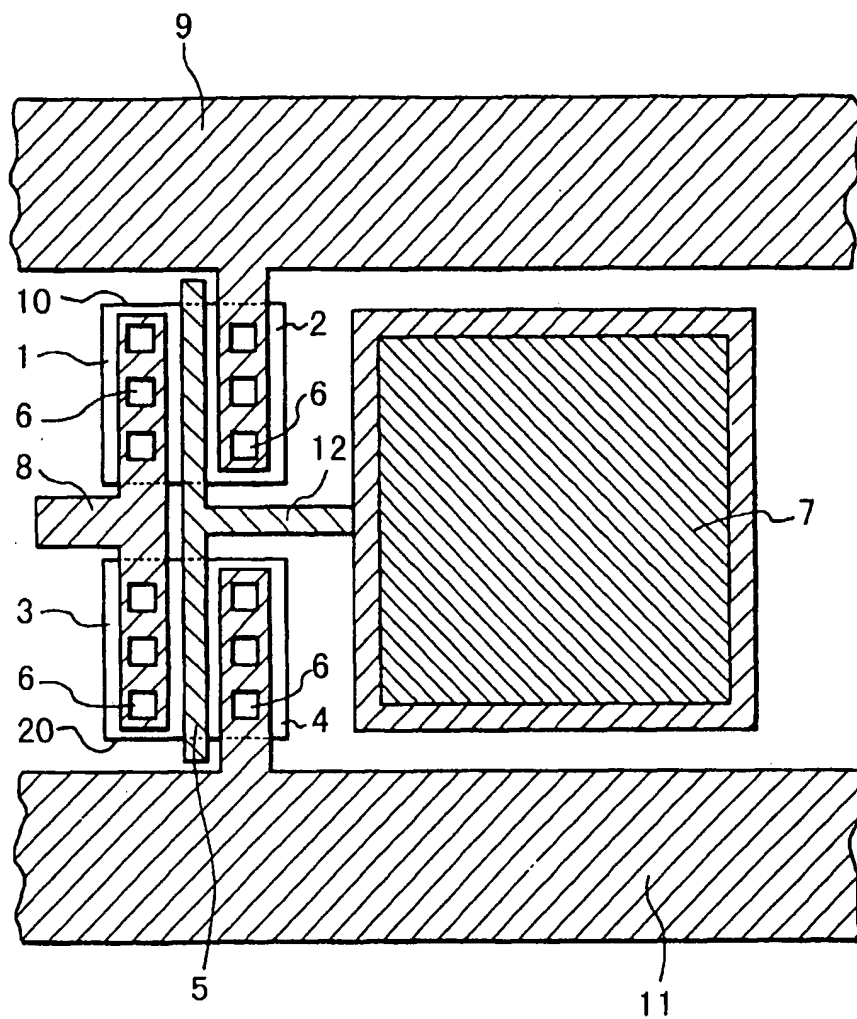


FIG. 3

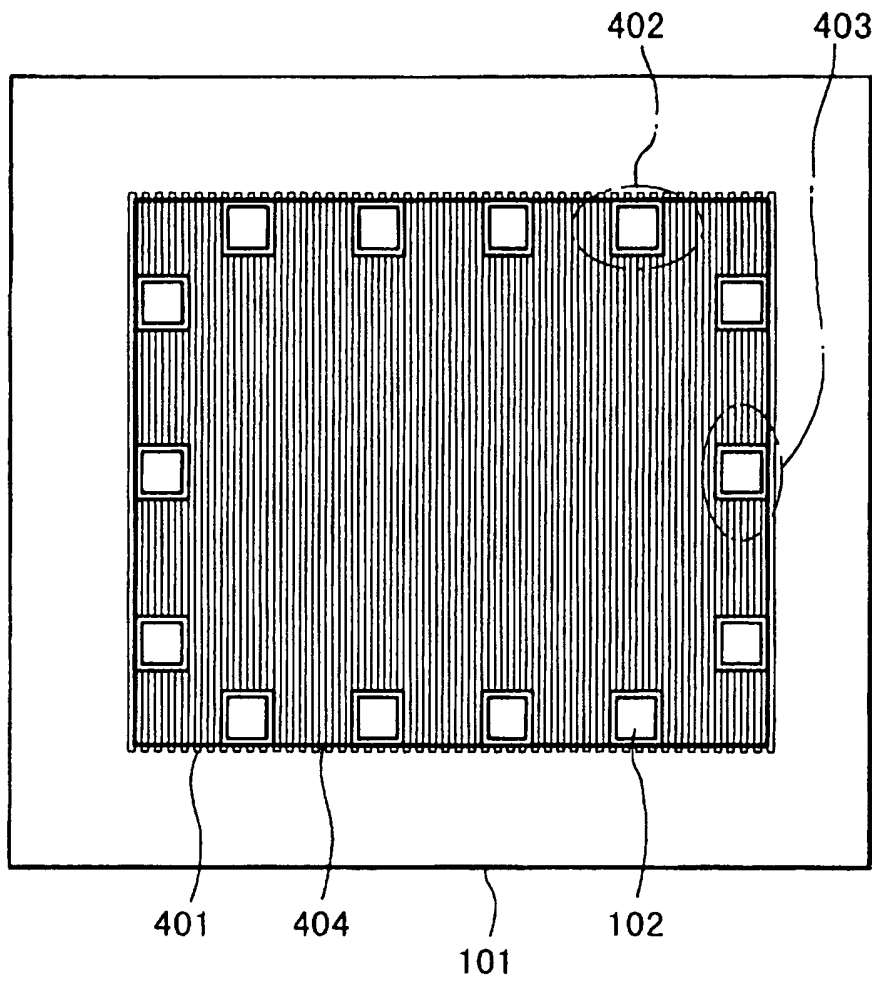


FIG. 4

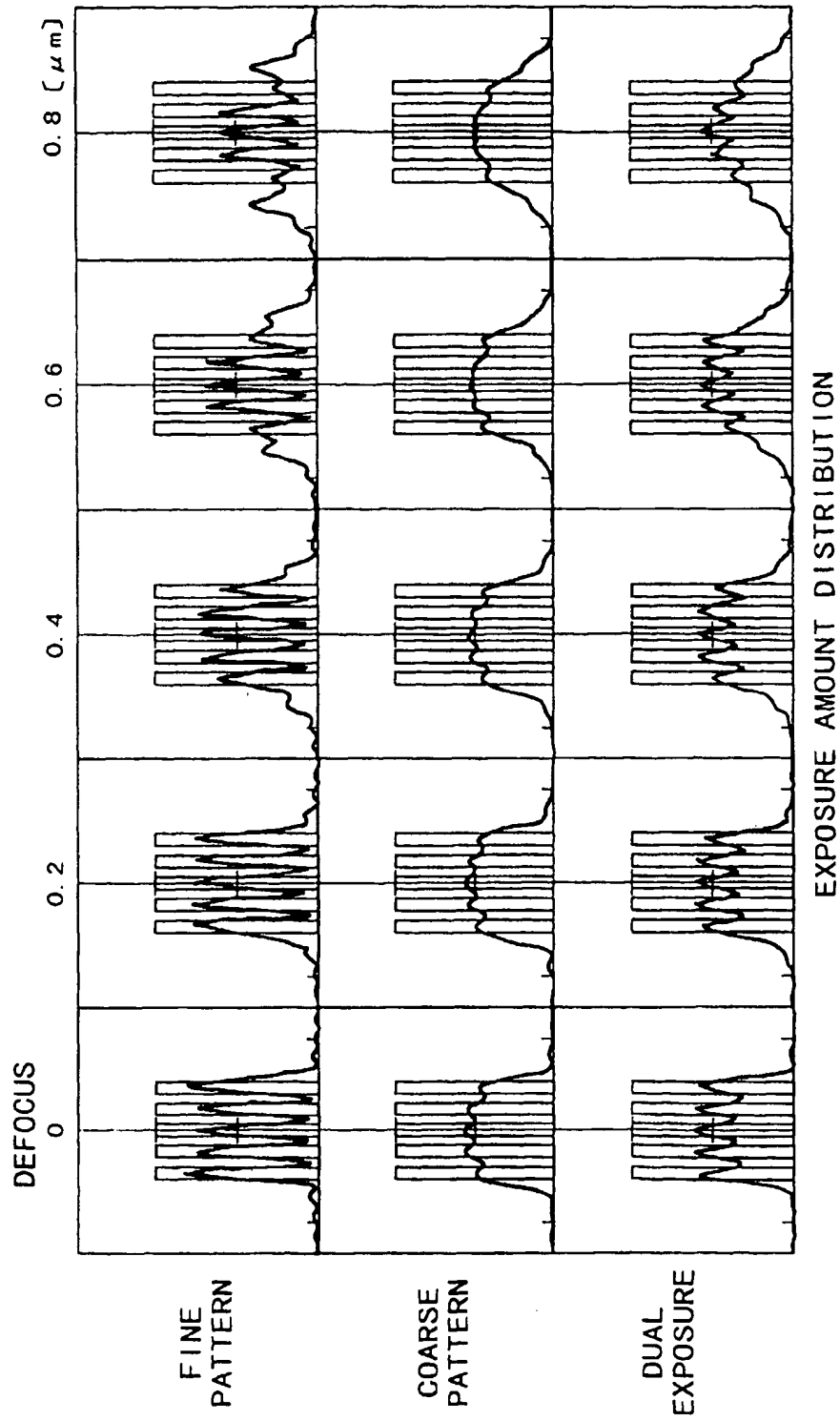


FIG. 5

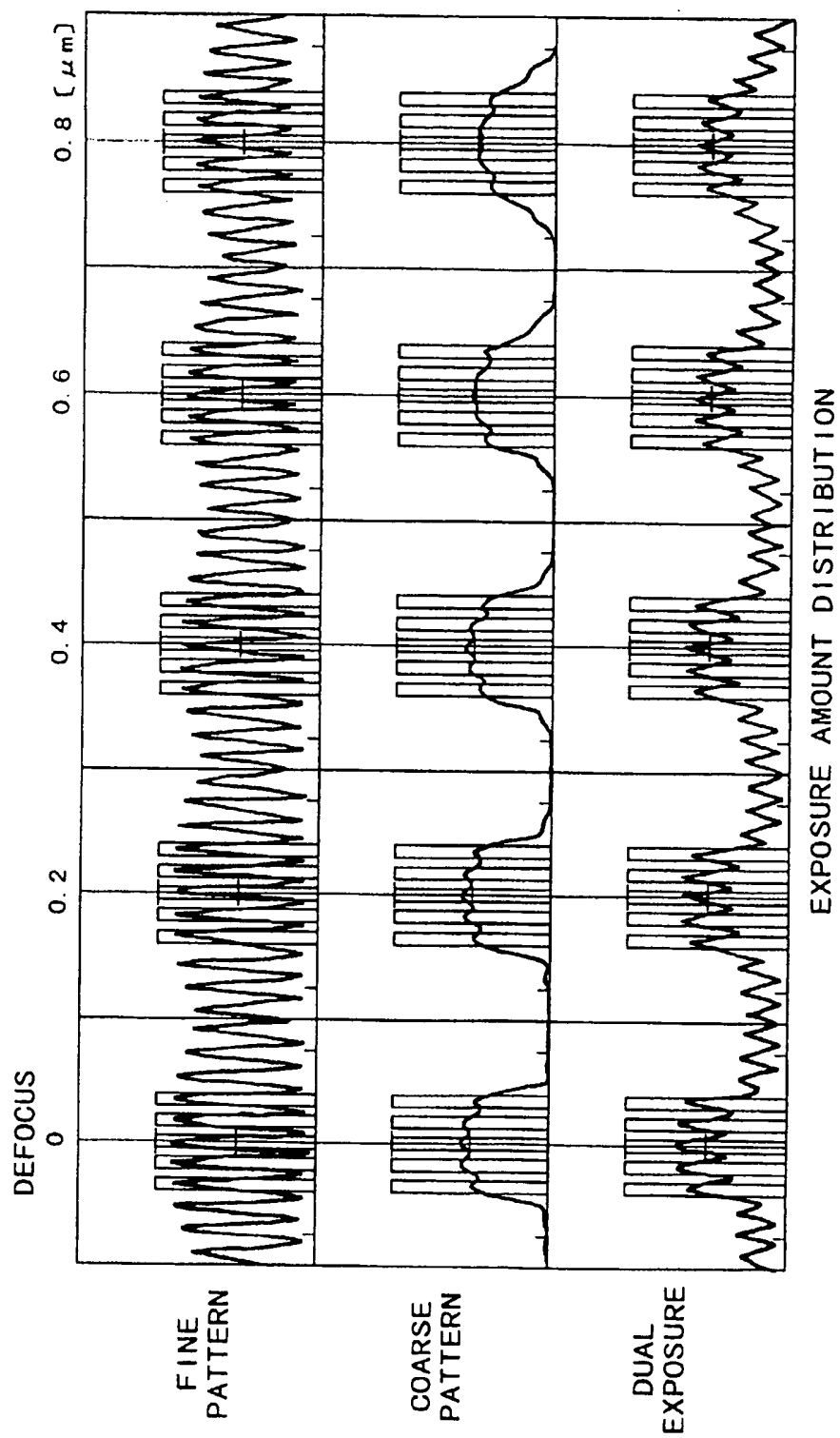


FIG. 6

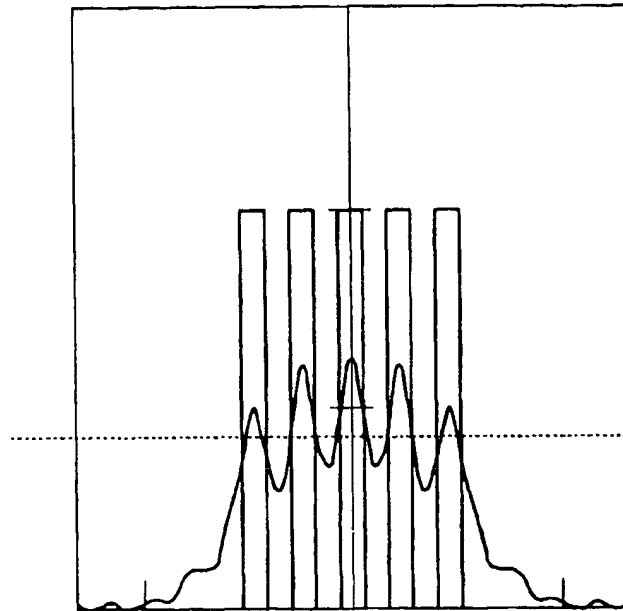


FIG. 7A

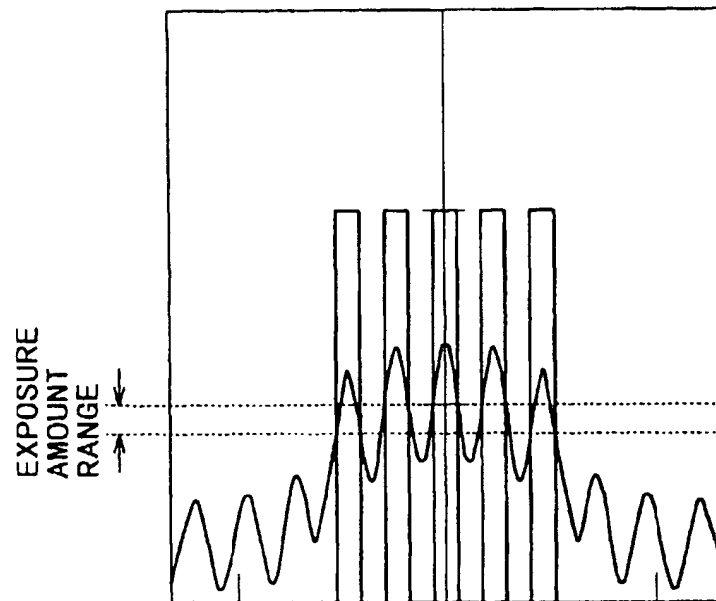


FIG. 7B

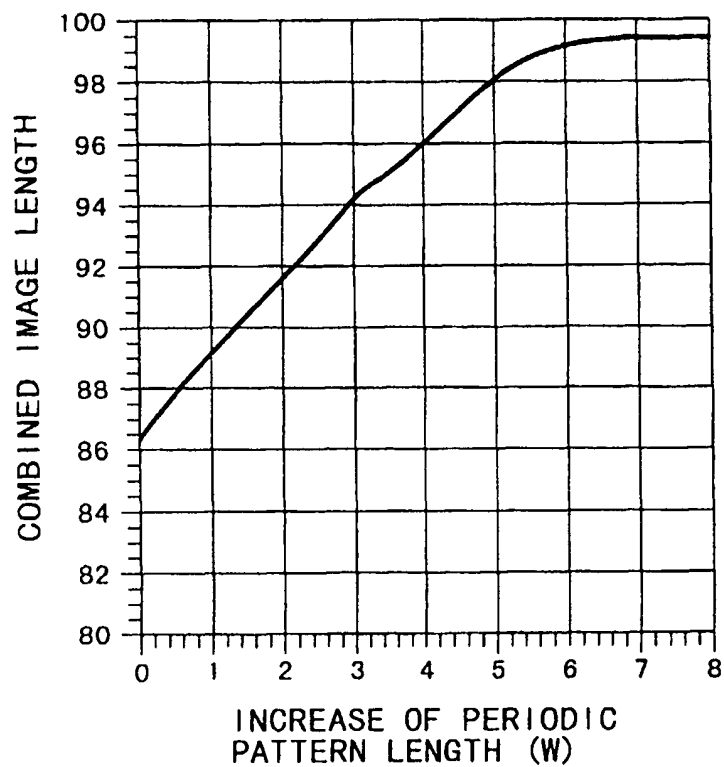


FIG. 8

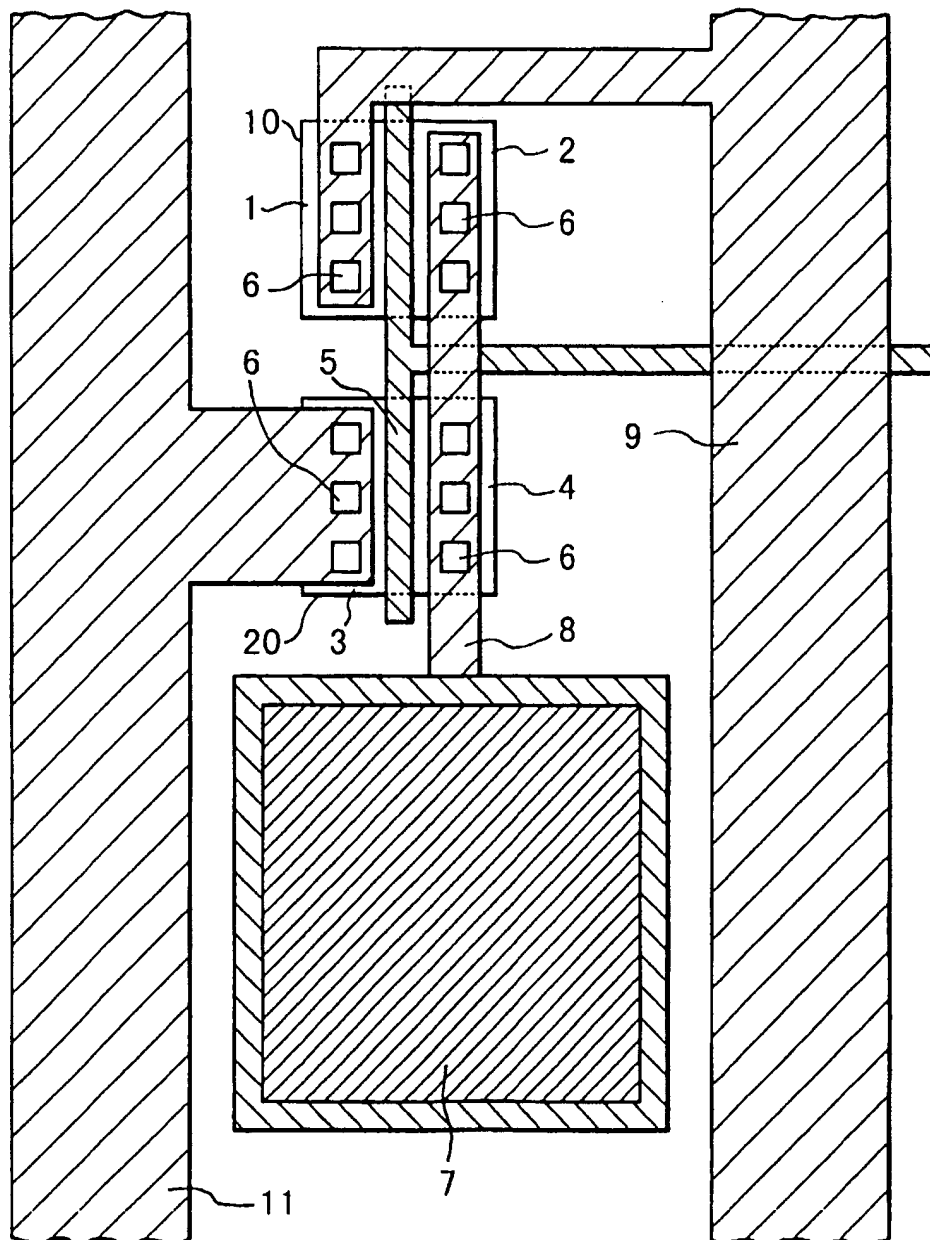


FIG. 9

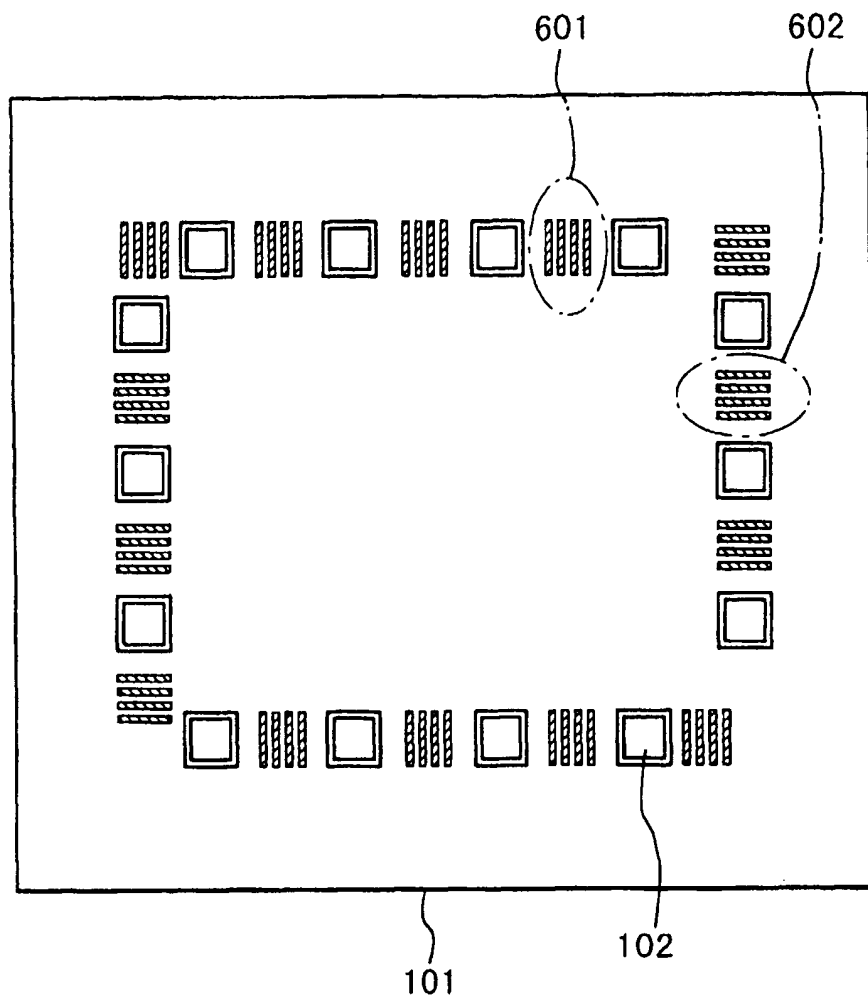


FIG. 10

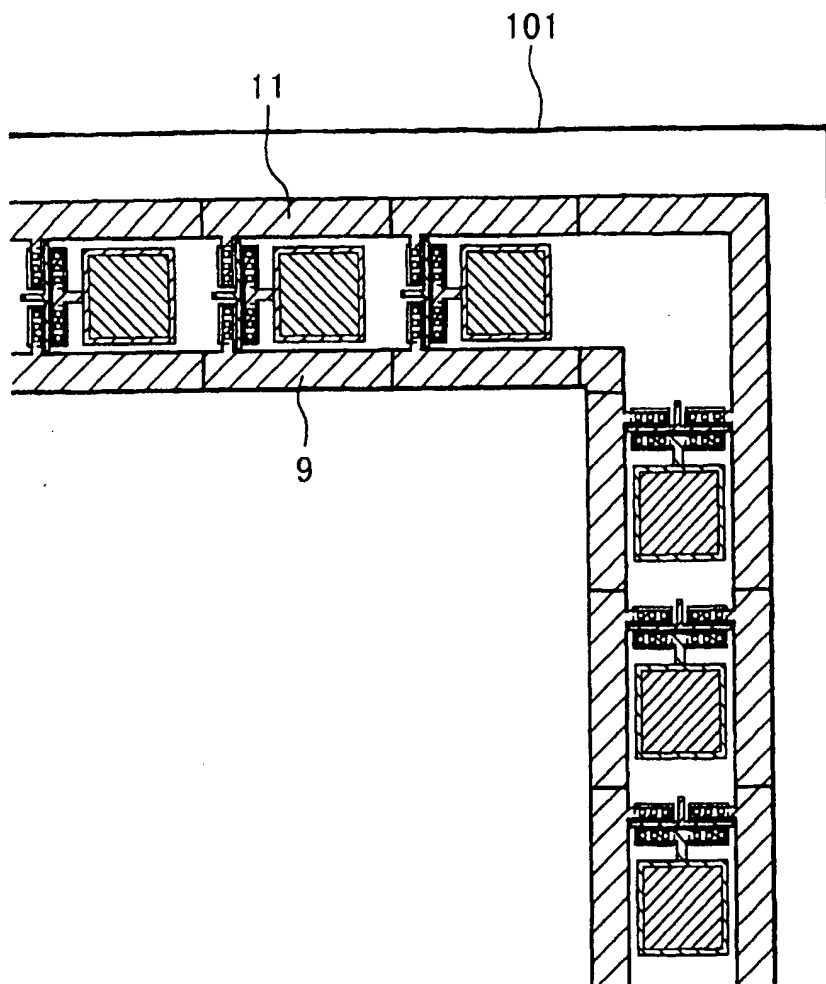


FIG. 11

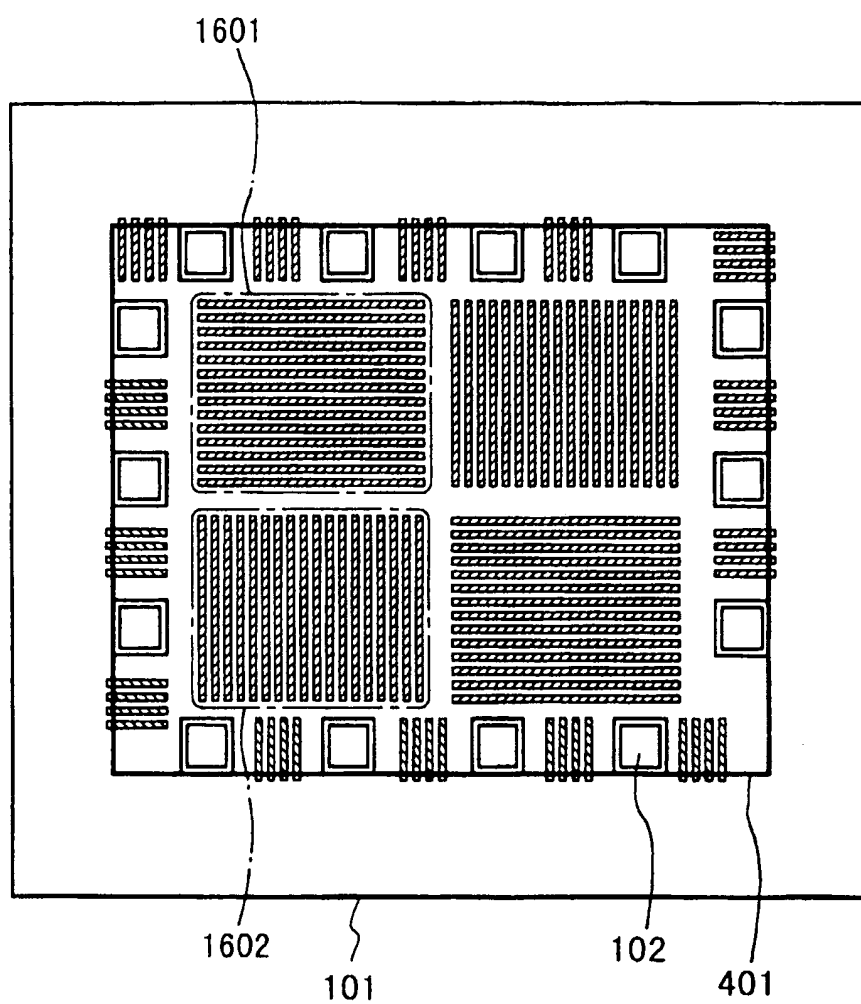


FIG. 12

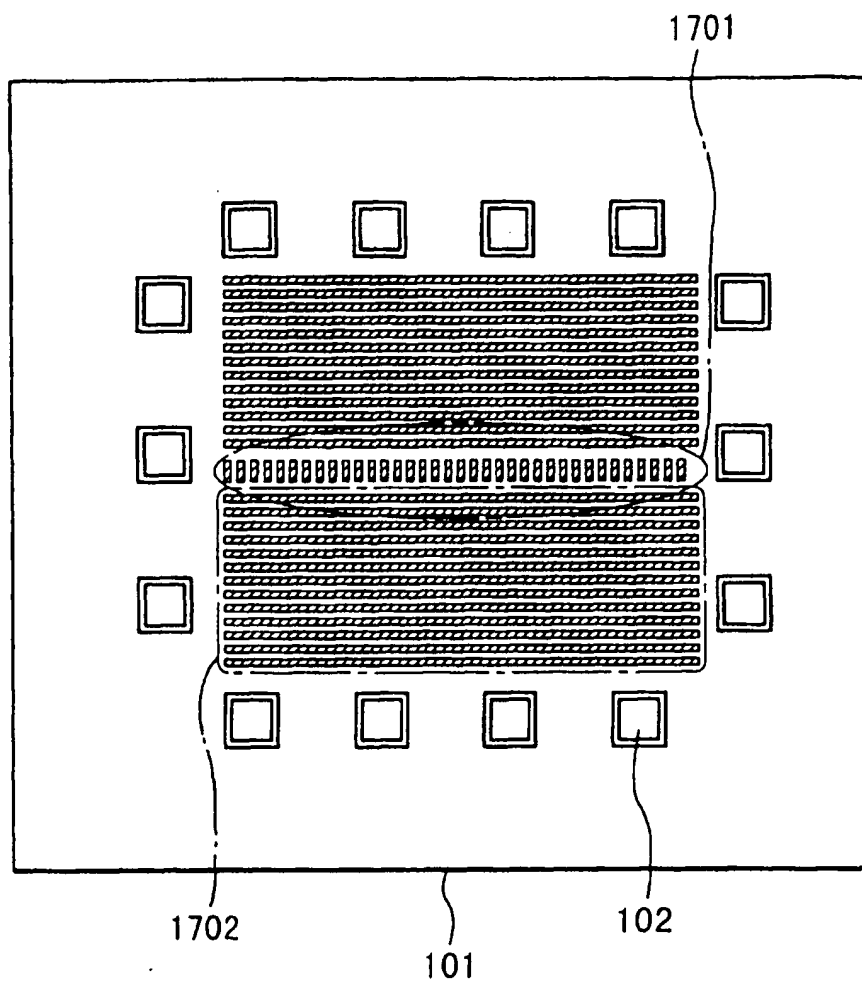


FIG. 13

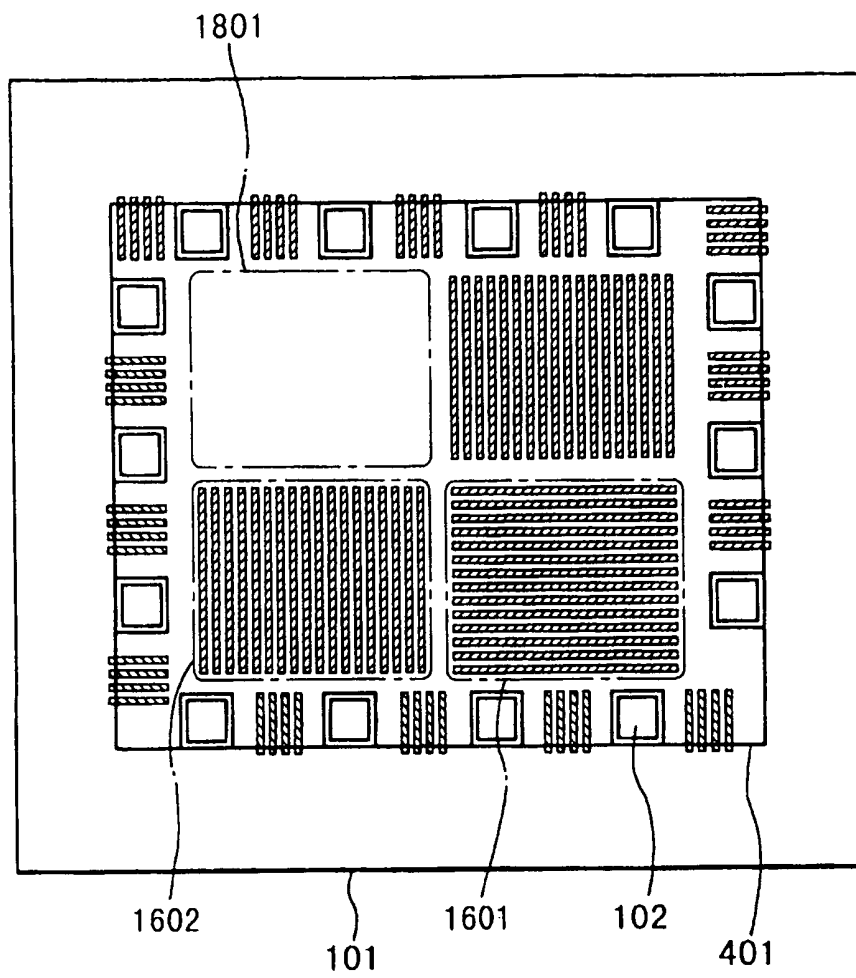


FIG. 14

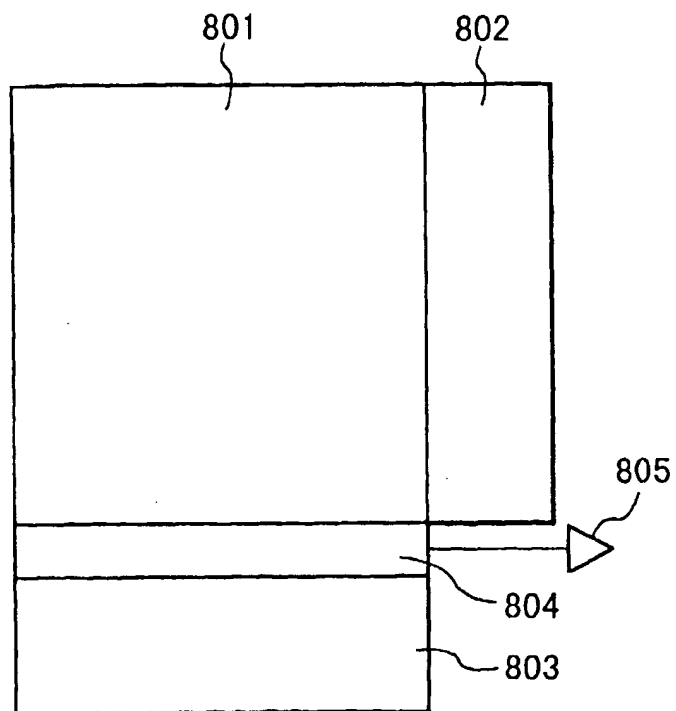


FIG. 15

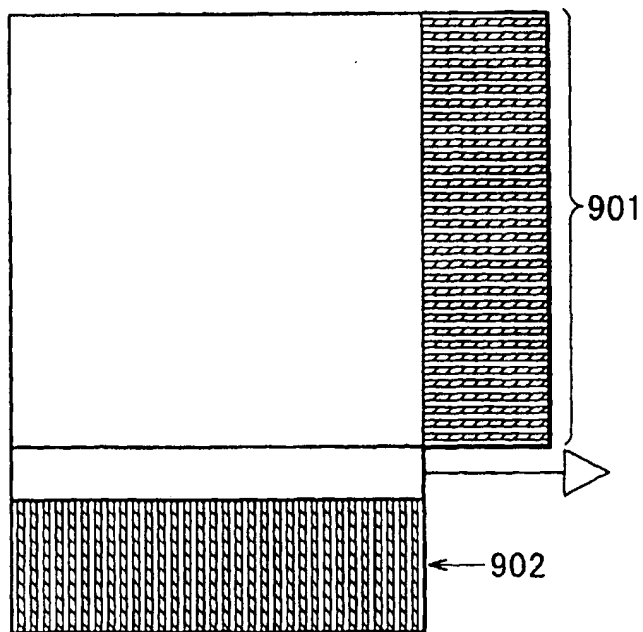


FIG. 16

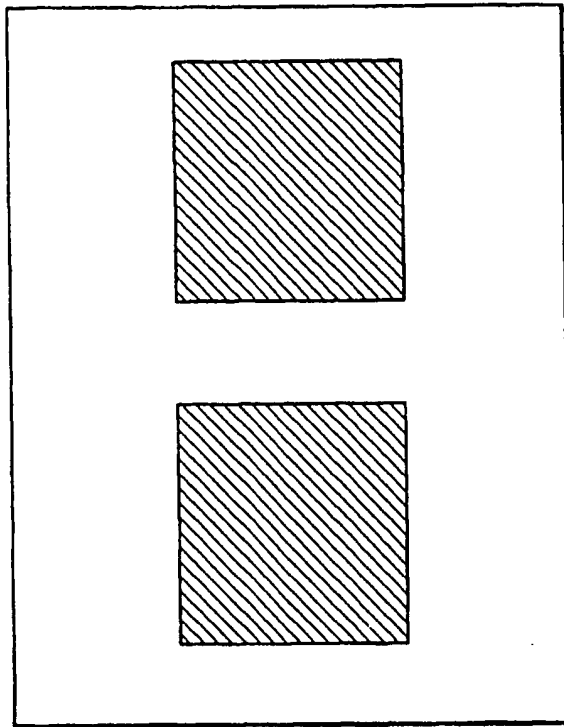


FIG. 17A

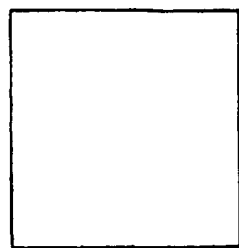
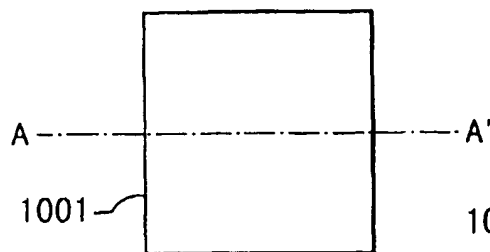


FIG. 17B

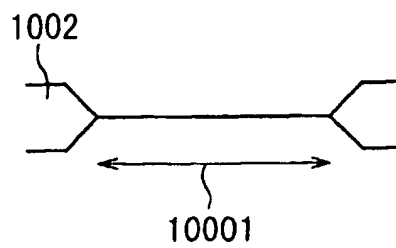


FIG. 17C

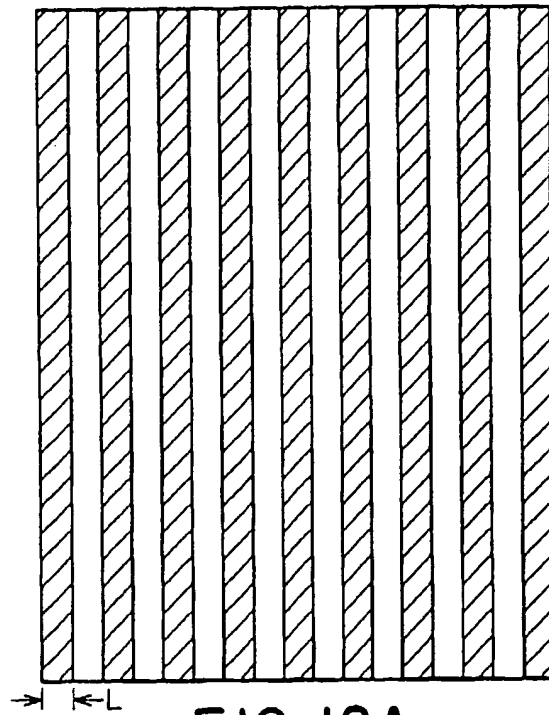


FIG. 18A

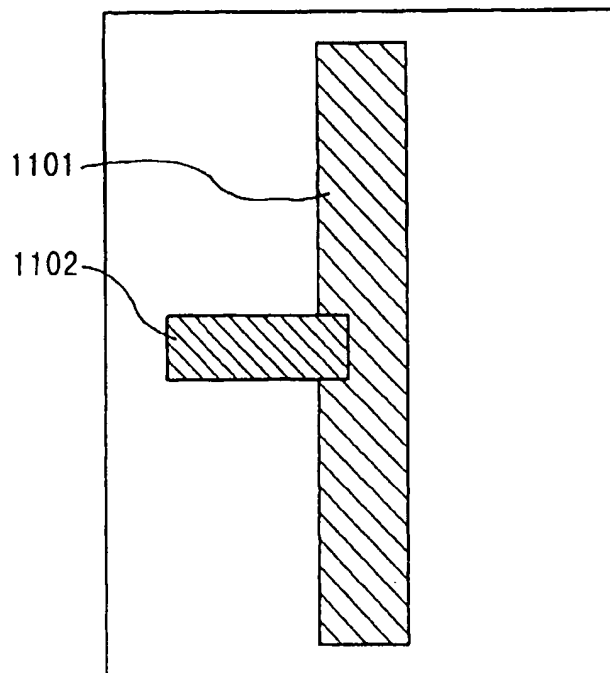


FIG. 18B

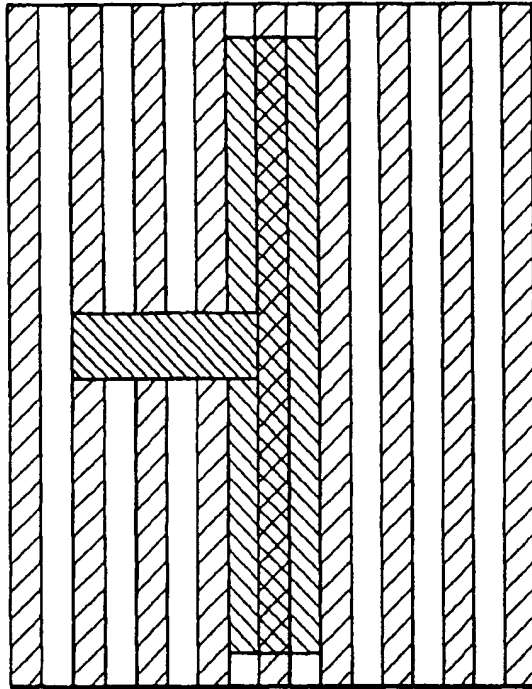


FIG. 19A

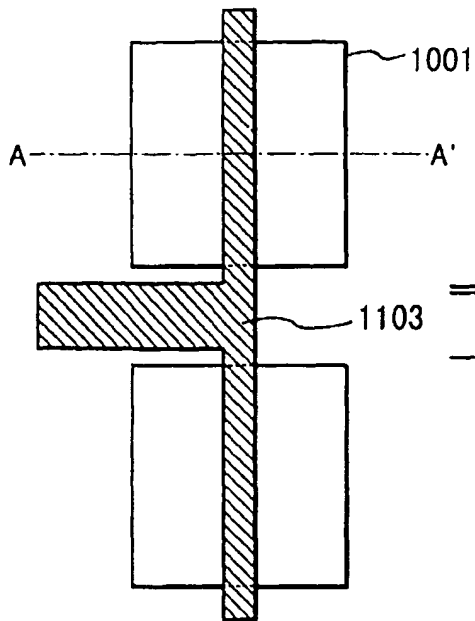


FIG. 19B

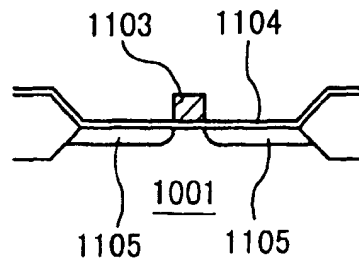


FIG. 19C

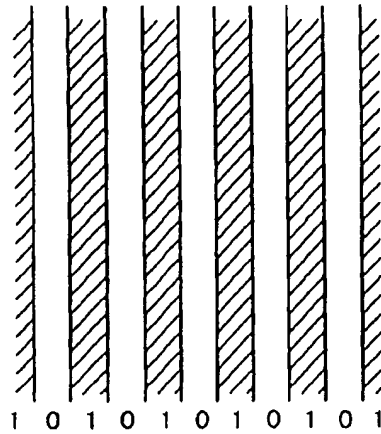


FIG. 20A



FIG. 20B

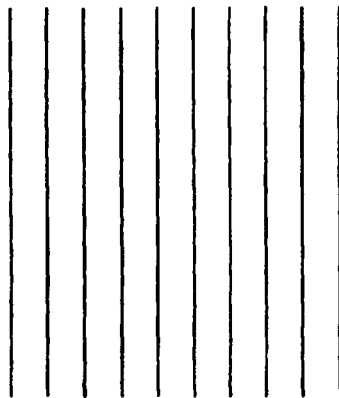


FIG. 21A

$$E = E_1 + E_2 \quad (E_2 = 0)$$

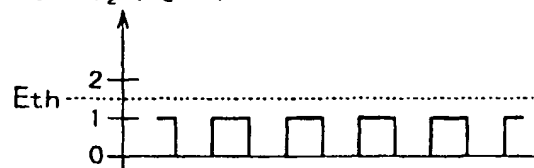


FIG. 21B

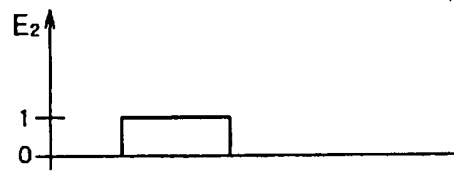
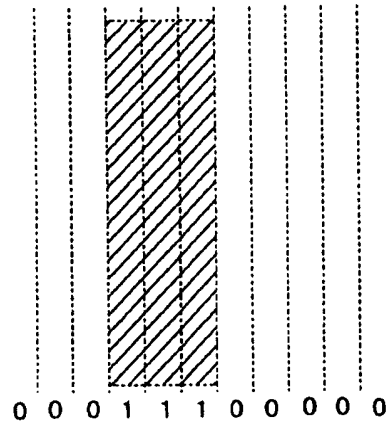


FIG. 22A

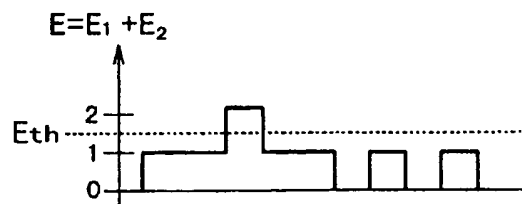
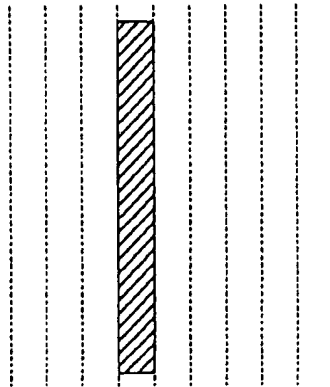


FIG. 22B

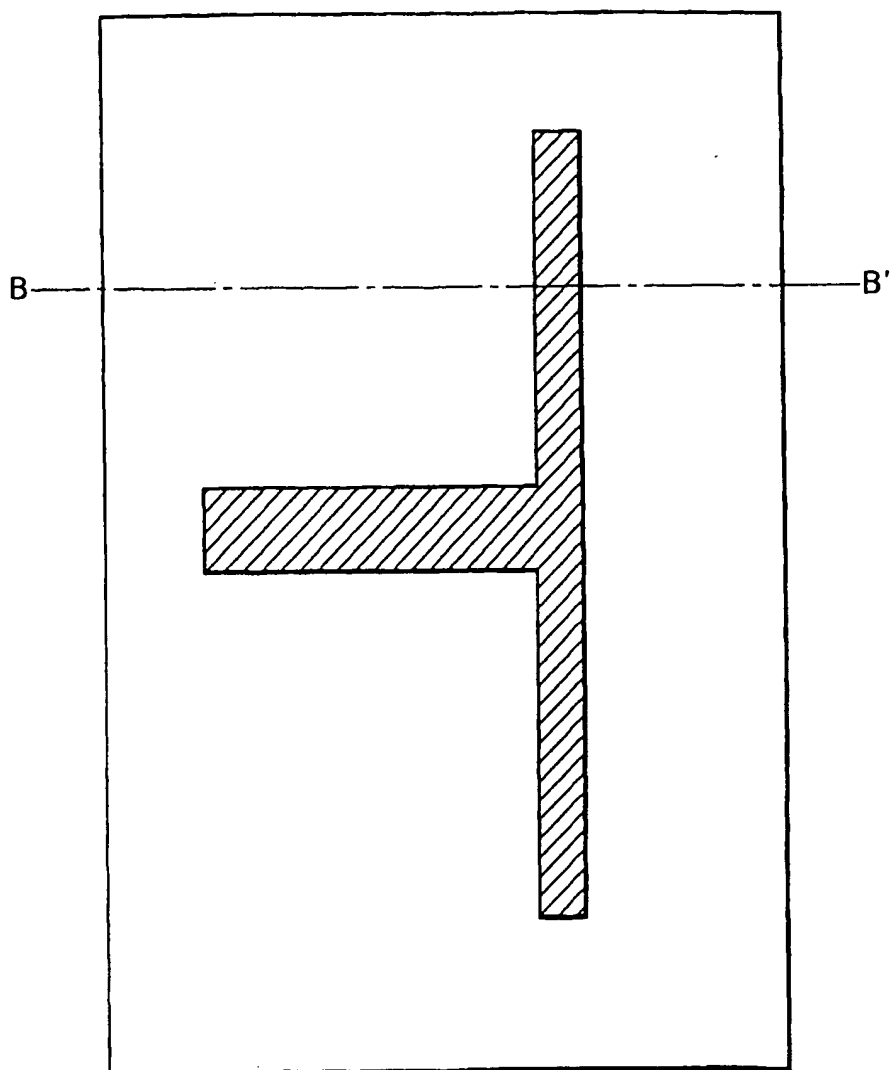


FIG. 23

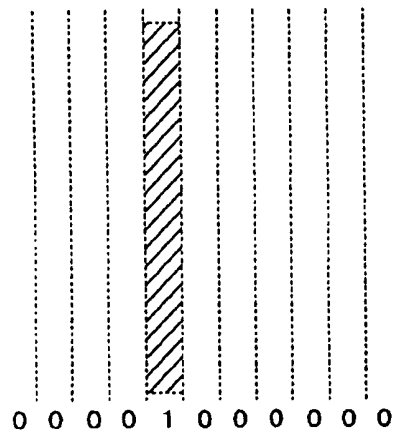


FIG. 24A

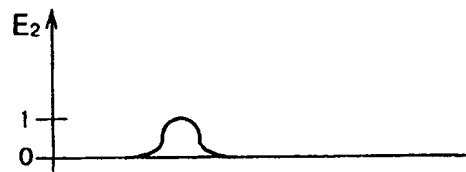


FIG. 24B

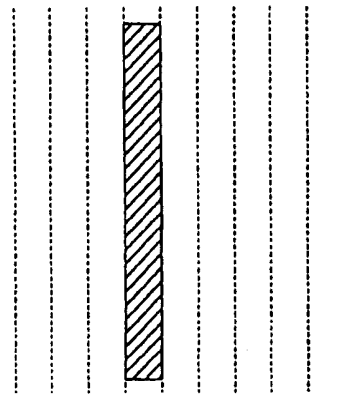


FIG. 24C

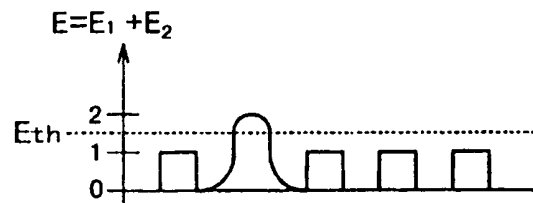


FIG. 24D

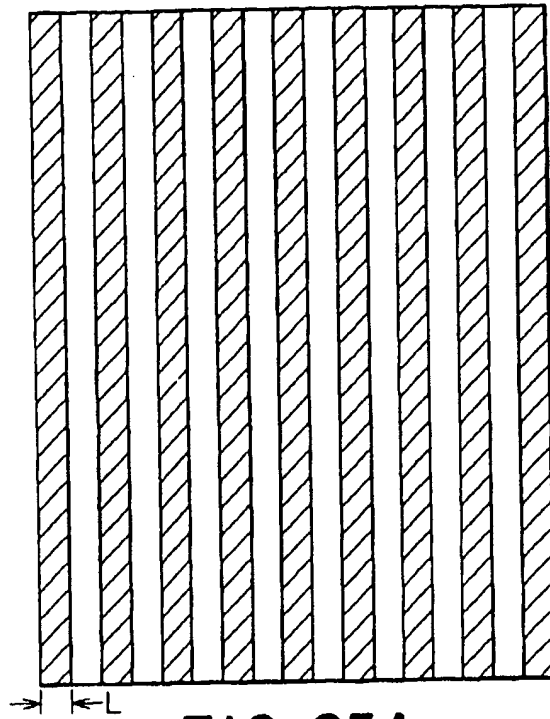


FIG. 25A

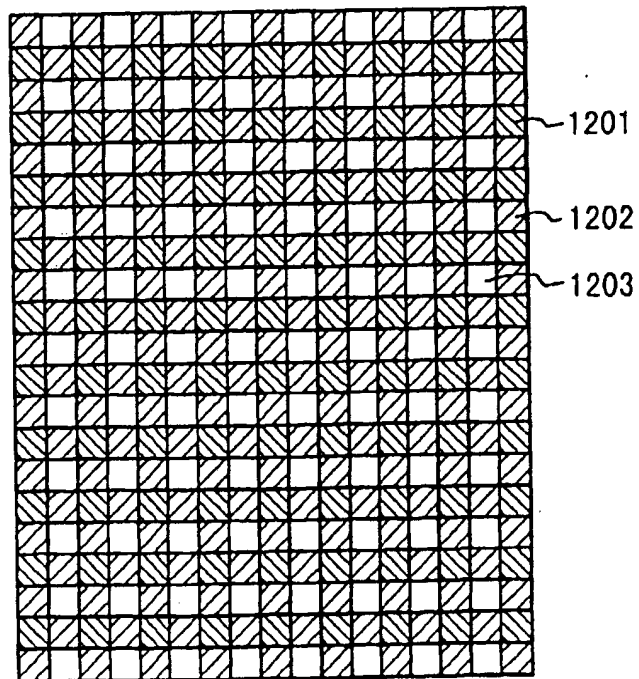


FIG. 25B

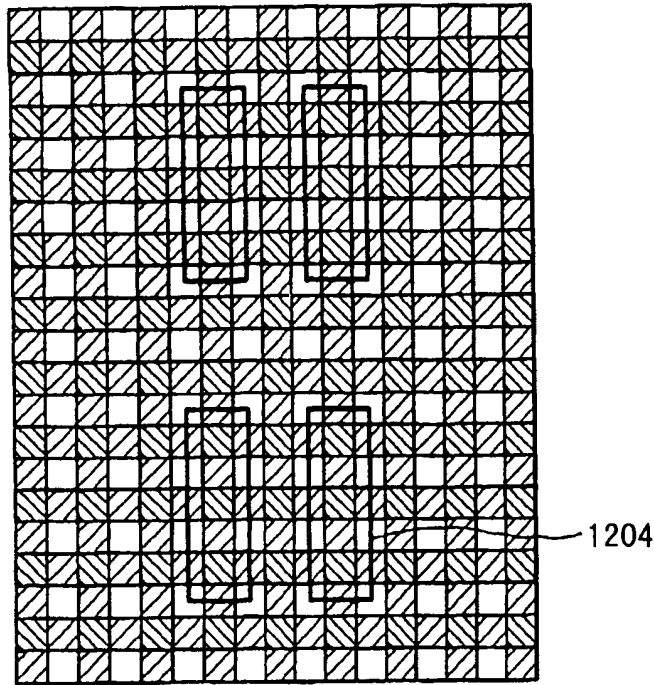


FIG. 26A

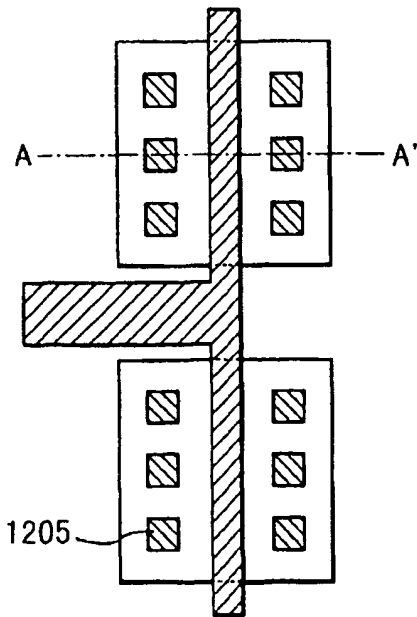


FIG. 26B

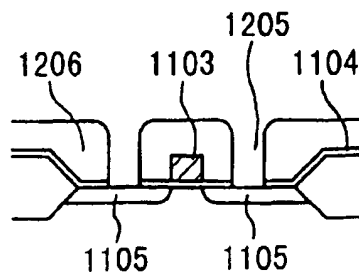


FIG. 26C

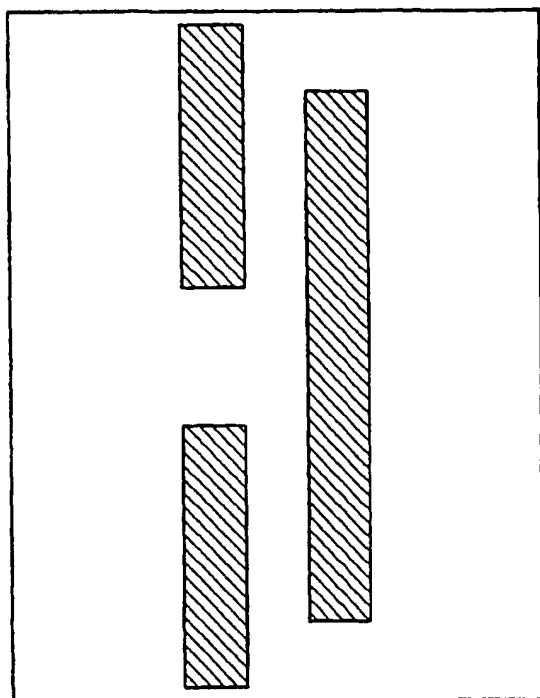


FIG. 27A

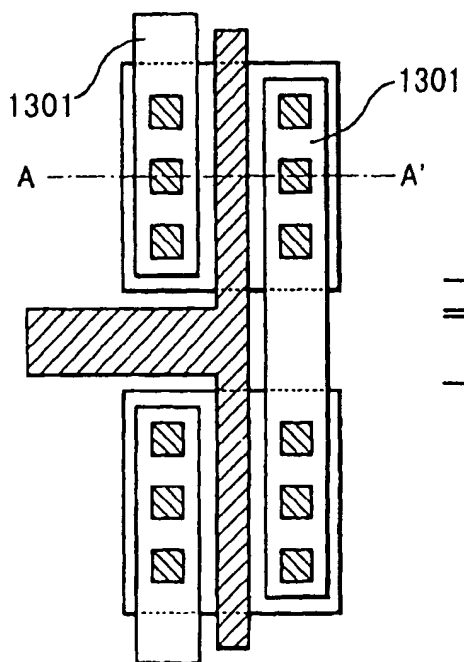


FIG. 27B

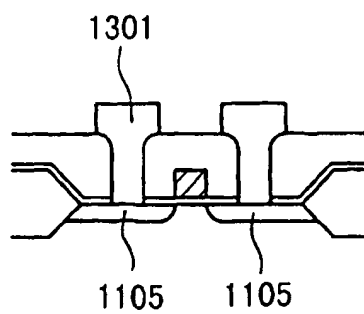


FIG. 27C

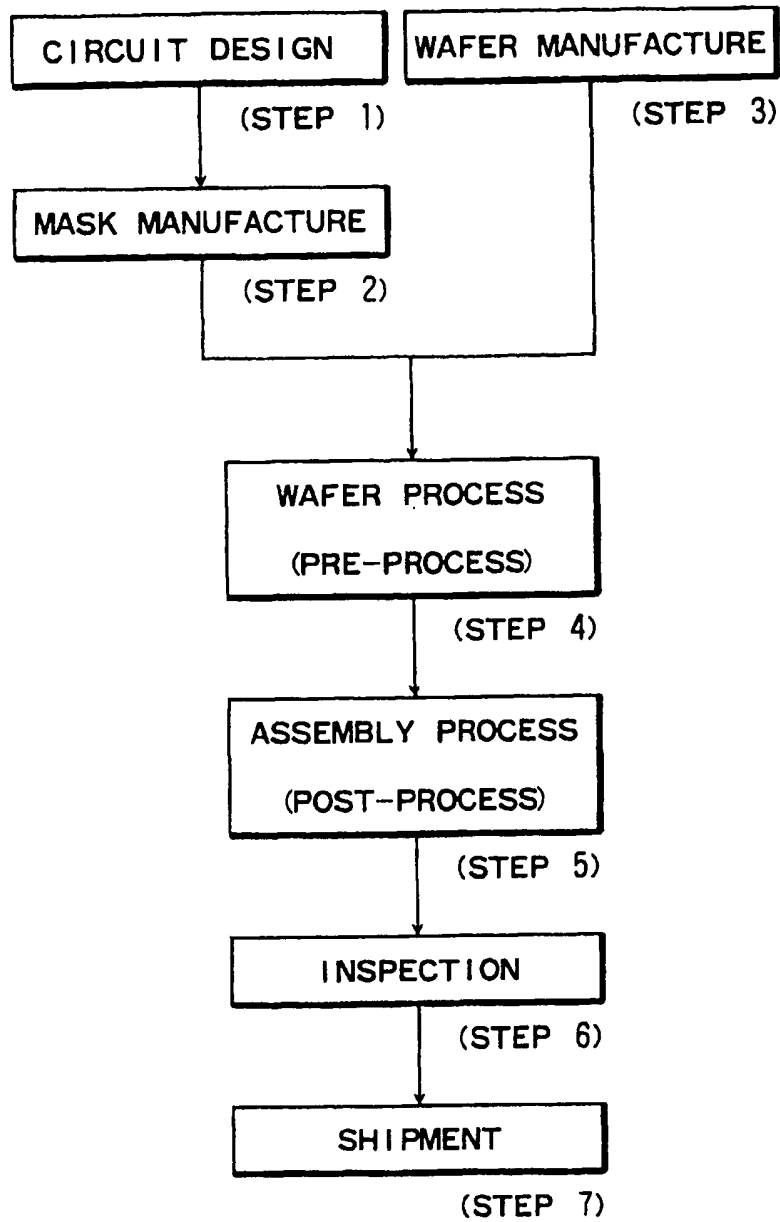


FIG. 28

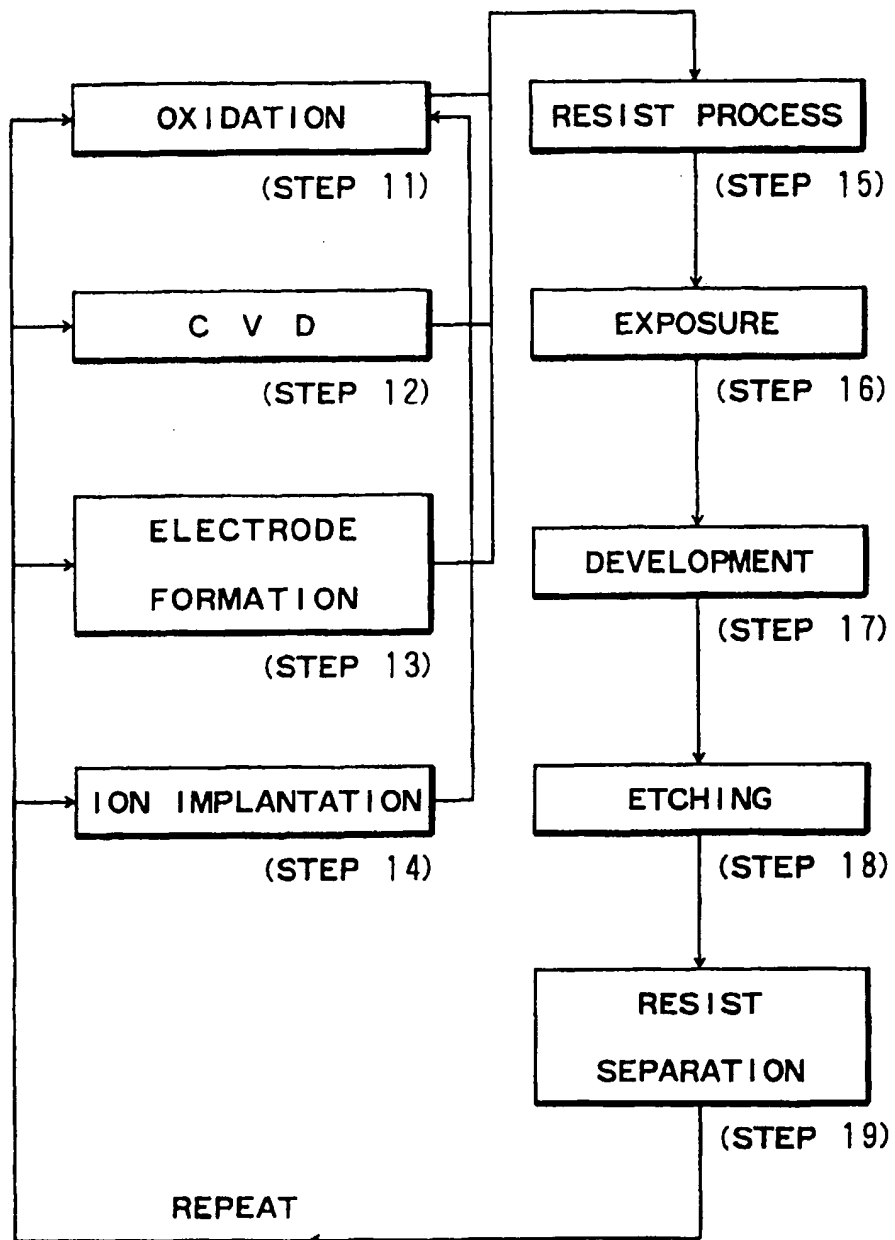


FIG. 29

THIS PAGE BLANK (USPTO)

**This Page is Inserted by IFW Indexing and Scanning
Operations and is not part of the Official Record**

BEST AVAILABLE IMAGES

Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images include but are not limited to the items checked:

- ☐ **BLACK BORDERS**
- ☐ **IMAGE CUT OFF AT TOP, BOTTOM OR SIDES**
- ☐ **FADED TEXT OR DRAWING**
- ☐ **BLURRED OR ILLEGIBLE TEXT OR DRAWING**
- ☐ **SKEWED/SLANTED IMAGES**
- ☐ **COLOR OR BLACK AND WHITE PHOTOGRAPHS**
- ☐ **GRAY SCALE DOCUMENTS**
- ☐ **LINES OR MARKS ON ORIGINAL DOCUMENT**
- ☐ **REFERENCE(S) OR EXHIBIT(S) SUBMITTED ARE POOR QUALITY**
- ☐ **OTHER:** _____

IMAGES ARE BEST AVAILABLE COPY.

As rescanning these documents will not correct the image problems checked, please do not report these problems to the IFW Image Problem Mailbox.

THIS PAGE BLANK (USPTO)